Anonymous Referee #1

We thank the reviewer for the very insightful comments. We respond to each comment below. Reviewer comments are in black. Our responses are in blue, and changes/additions to the manuscript are in *italics*.

Review of the manuscript "SOA formation from the photooxidation of α -pinene: systematic exploration of the simulation of chamber data"

General comments:

This manuscript presents results from simulations of Caltech smog chamber experiments on photooxidation of α-pinene with the Generator for Explicit Chemistry and Kinetics of Organics in the Atmosphere (GECKO-A). The manuscript is well written and present interesting and new experimental and theoretical results on the SOA formation from photooxidation of α -pinene at different OH concentrations. The authors perform an extensive set of sensitivity tests in order evaluate the relative role of VOC chamber wall losses, gas to particle mass transfer limitations, second and later generation oxidation products, condensed-phase photolysis and particle-phase dimerization for the SOA formation. However, according to my opinion no one of the suggested model setups is able to capture the observed evolution of the SOA formation in a convincing way for all experiments. Instead the model always tends to overestimate the SOA formation during the high OH concentration experiments and underestimate the SOA formation during the low OH concentration experiments. As the authors suggest this can possibly be because the model do not take into account the autoxidation of α -pinene and formation of first generation ELVOC oxidation products. Most of the sensitivity tests are well motivated and described but I have a few critical questions (comments) that I would like the authors to answer (consider). If this is done in an appropriate way I think the manuscript is well worth to be published in ACP.

We agree that none of the hypotheses we investigate fully explains all features of the observed SOA formation. We thank the reviewer for the comments regarding autoxidation and discuss these below. With the additional discussion of autoxidation, we believe a convincing case can be made for two of the hypotheses explaining part or all of the measurement-model discrepancy. We identify areas where additional study is needed in order to further evaluate these hypotheses.

Experiment 141125 has the highest SOA yield. Based on your modeled OH concentration of 2 x 10⁵ molec cm⁻³ you get an overall OH reaction rate of 10⁵ s⁻¹ (P 33177, L 7). I compared this with how much O₃ that needs to be present in order to get the same overall O₃ reaction rate as the OH reaction rate. My calculation gave that at an O₃ concentration of 4.5 ppbv half of the α -pinene is oxidized with O₃ instead of OH (ko₃ = 9.4 x 10⁻¹⁷ cm₃ molec-1). According to Fig. S2 the measured O₃ concentration increases from 0 to 10 ppbv during this experiment while the modeled O₃ concentration only reaches 4 ppbv in the end of the experiment. Thus, according to the measurements I think that more than half of the consumed α -pinene reacts with O₃ and not OH. How does the model handle the O₃ oxidation of α -pinene and the chemistry beyond the formation of the Criegee biradicals? How much SOA is formed from ozonolysis of α -pinene? This is not mentioned at all in the manuscript but could potentially be a large source of error that need to be discussed. I think it is suitable to add figures to the supplementary material that shows how large fraction of the α -pinene that react with O₃ according to both the model and the measurements. Because the autooxidation mechanism that is suggested to generate ELVOCs is much more

effective when α -pinene is oxidized by O₃ instead of OH I think this could at least partly explain why the model and measurements disagree. This needs to be estimated and discussed.

We agree that ozonolysis likely explains part of the measurement-model discrepancy at low UV. A discussion of the ozonolysis of α -pinene has been added to section 2.1 along with a figure in the Supplement:

Ozonolysis chemistry in GECKO-A does not explicitly include the Criegee biradicals formed from the addition of O_3 to the α -pinene double bond; rather the predicted products of the Criegee intermediates are directly assigned to the α -pinene ozonolysis reaction. This simplification overlooks potential reactions of the stabilized Criegee intermediates (SCI) with water, alcohols, acids, carbonyls, etc. (Ma et al., 2008; Tobias and Ziemann, 2001). Reaction of the SCI with water to form pinonaldehyde is thought to be significant (Capouet et al., 2008), and a direct route to pinonaldehyde has been added in GECKO-A. The initial reaction step for ozonolysis is shown in Fig. S1. Furthermore, Ma et al. (2008) proposed several later-generation intramolecular isomerization reactions to form low-volatility acids. These reactions have been implemented in GECKO-A as a sensitivity test. Virtually no change in predicted SOA concentrations is observed when adding these reactions or when changing the branching ratios of the SCI products. Separate (not shown) purely ozonolysis simulations showed very little SOA formation, indicating potential missing pathways in the ozonolysis mechanism forming low-volatility products. Updating the ozonolysis mechanism should be the subject of future studies.

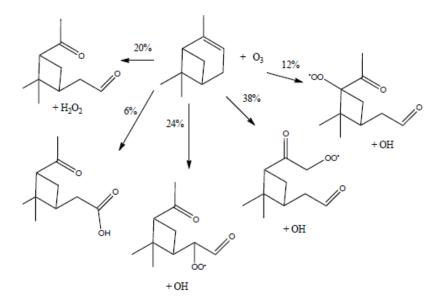


Figure S1: Overview of the α -pinene + O₃ initial reaction step in GECKO-A. All subsequent chemistry is generated according to the standard protocols in GECKO-A.

A plot has been added to the Supplement showing how much α -pinene reacts with OH vs. O₃ along with the following explanation in section 4 of the main text:

Figure S5 shows the amount of α -pinene predicted to react with OH vs. O_3 , using both the modeled and measured O_3 concentration. For the 100% UV experiments, ~2-3% of the total α -pinene is predicted to react with O_3 , using either the modeled or measured O_3 concentration. For the 10% UV experiments, ~20% of the total α -pinene is predicted to react with O_3 using the modeled O_3 concentration. For experiment 141113, roughly the same amount of α -pinene is predicted to react with O_3 based on the measured O_3 concentration. However, for experiment 141125, because the model underpredicts the O_3 concentration, much more α -pinene is predicted to react with the measured O_3 concentration, ~49 %.

Figure S5 is shown on the following page.

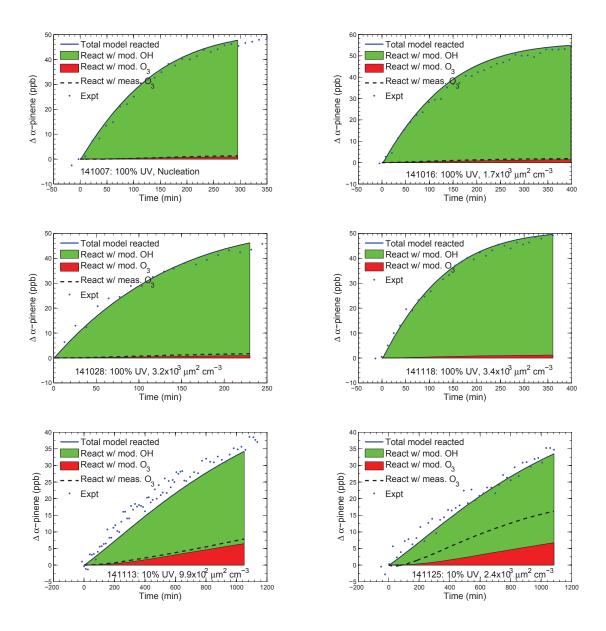


Figure S5: Amount of α -pinene predicted to be reacted with OH versus O₃, for both modeled and measured O₃ concentrations. The solid blue line shows the total α -pinene reacted. The green area shows the amount reacted with OH based on the modeled OH concentration. The red area shows the amount reacted with O₃ based on the modeled O₃ concentration. The dashed black line shows the amount predicted to have reacted with the measured O₃ concentration. Because the O₃ monitor malfunctioned during experiment 141118, the dashed line is not shown for this experiment.

Section 5.4 discussing autoxidation has been significantly expanded:

Moreover, during the low UV experiments, 20-50% of α -pinene reacts with O_3 instead of OH, compared to only 2-3% for the high UV experiments. As discussed previously, the ozonolysis mechanism in GECKO-A is likely incomplete and may be lacking pathways to SOA precursors, such as autoxidation. Because autoxidation is much more efficient from the ozonolysis pathway than from the OH pathway (Ehn et al., 2014; Jokinen et al., 2014), more ELVOCs will likely be produced under low UV and will increase the amount of SOA formed. Furthermore, autoxidation could also explain the difference in SOA yield observed between the two low UV experiments. Experiment 141125 has a higher yield than experiment 141113 and also has a higher observed O_3 concentration. ELVOC production was likely higher during this experiment owing to the increased fraction of α -pinene reacted via ozonolysis.

Autoxidation is observed to occur immediately upon oxidation (Rissanen et al., 2015), indicating it is likely a first-generation process. Second-generation species are predominantly responsible for the discrepancy in model predictions between high and low UV due to the difference in OH levels (Fig. 4). Unlike second-generation products, autoxidation products will not depend on the OH concentration and will not be produced slower under low UV. Therefore, adding autoxidation pathways will likely increase the fraction of SOA composed of first-generation products, which may lead to similar predictions for high and low UV.

However, explicit mechanisms and rate constants are still lacking for autoxidation in the α pinene system, although they have been developed for simpler cycloalkenes (Mentel et al., 2015; Rissanen et al., 2015). A recent computational study found that the cyclobutyl ring in α -pinene must open in order for intramolecular hydrogen shifts to be competitive with the peroxy bimolecular sink reactions (Kurtén et al., 2015). The currently-accepted α -pinene ozonolysis mechanism does not include rapid opening of this ring. Kurtén et al. (2015) investigated several pathways to break this ring but found none that could explain all of the characteristics of observed ELVOCs from α -pinene. In the absence of explicit mechanisms, the effect of autoxidation cannot be fully tested. To approximate the effect, a C₁₀H₁₅O₉ species (an ELVOC predicted by Kurtén et al. (2015)) is added with a 7% molar yield (based on the 6-8% yield measured by Ehn et al. (2014)) as a direct product from the α pinene+O₃ reaction. This addition has no effect on SOA concentrations for the high UV experiments but increases the final SOA concentrations for the low UV experiments by ~10 μ g m⁻³ (not shown). *However, adding this fixed ELVOC yield does not increase SOA predictions for low UV at the* beginning of the experiment, when no O_3 is present. Therefore, although autoxidation via ozonolysis is likely important towards the end of the low UV experiments, other explanations are needed to reconcile the underprediction of SOA at the start of the experiment. Autoxidation via OH oxidation could potentially resolve part of this discrepancy, but no pathways or yields are yet available. Overall, autoxidation is a likely process to explain the measurement-model discrepancy at high and low UV but is in need of more study. The presence of significant autoxidation could furthermore lead to a different best-fit vapor wall loss rate.

A sentence has been added to the abstract emphasizing the potential importance of autoxidation:

Moreover, we propose that autoxidation may alternatively resolve some or all of the measurementmodel discrepancy, but this hypothesis cannot be confirmed until more explicit mechanisms are established for α -pinene autoxidation.

On page 33169, L10-12 you write that the particle number concentration remains unchanged in the model during the course of the experiments. Why do you not include particle wall losses in the

model? On page 33173, L1-2 you write that the measured particle volume distributions are corrected with the size-dependent wall loss rates. Thus, it should be straightforward to also consider these particle wall losses in the model.

We do not include particle wall losses in the model because the particle size distribution is not explicitly simulated. Only a single size bin is used so that all particles have the same radius (see below). Only the particle radius, which changes with time as condensation occurs, is tracked. Including size-dependent particle wall loss for a single particle bin could potentially over- or underestimate the amount of particle wall loss occurring because the true size distribution is not represented. Furthermore, to include particle wall loss, we would have to include a means to track the organic aerosol that deposits on the wall separate from the organic aerosol that remains suspended. GECKO-A is not currently well-equipped to handle that addition. Because SOA formation in this system does not display a dependence on particle surface area, we are confident that not including particle wall loss does not significantly affect our SOA predictions.

I guess that the observed SOA growth curves displayed in e.g. Fig. 2 and 4 are not what actually were observed but the wall loss corrected SOA mass derived from the SMPS measurements. You need to explicitly write this in the manuscript. I also wonder how uncertain the corrected SOA mass is. How much did you need to correct the measured SMPS particle volume? I know from experience that chamber wall losses in Teflon smog chambers can vary from experiment to experiment because of e.g. variations in the electrical field strength of the chamber and how long time it takes between that the seed particles are added to the SOA formation starts. I think you should add the not wall loss corrected SOA or total particle mass to the panels in Fig S3.

The reviewer is correct that all measured SOA data shown in the manuscript have been particlewall-loss corrected. We revised Fig. S3 (now Fig S2) to show the non-particle-wall-loss corrected total particle volume, as well as the total volume corrected with both the lower and upper bound (shown on following page). It is not possible to show the non-wall-loss corrected SOA; the DMA only measures the total volume of the particles, which is a mixture of organic aerosol and inorganic seed. Only by accounting for particle wall loss can the seed volume be subtracted. An explanation of this has been added to section 4:

Measured volume distributions must be corrected for particle wall loss; the DMA measures the total volume of particles, which is a mixture of organic aerosol and inorganic seed. By accounting for particle wall loss, the seed volume can be subtracted and the mass of SOA calculated.

Uncertainties in the particle wall loss correction of the data arise primarily from the assumption in terms of interactions of deposited particles on the wall with suspended vapors. As we stated in the main text: 'in the lower bound, once deposited, particles are assumed to no longer interact with the vapor. The mass of SOA present on a particle at the moment of its deposition is added when calculating the total SOA. In the upper bound, deposited particles are assumed to continue growing at the same rate as suspended particles, and this SOA is similarly added to the total SOA.' As we show in Figure S2 in the supplement (formerly Figure S3), the derived total SOA mass may differ from 1% to 22% for the high UV experiments and 200% to 315% for the low UV experiments under these two assumptions. (The very large difference between the lower and upper bound for the low UV experiments is likely an artifact resulting from the small number of particles remaining at the end of the low UV experiments. This is explained in more detail in the caption of Figure S2). Another uncertainty is related to the surface properties of (NH₄)₂SO₄

particles and organic coated particles. We measured the size dependent deposition rates of dry $(NH_4)_2SO_4$ particles in the particle wall loss calibration experiments. We applied the measured rates to the actual α -pinene + OH experiments to derive the total SOA mass. While we used $(NH_4)_2SO_4$ as seeds to provide sufficient surface area for partitioning of organic vapors, these seed particles are eventually coated by an organic layer, which potentially alters the surface properties and may lead to a different wall accommodation coefficient. For now, we assume the accommodation coefficient for both $(NH_4)_2SO_4$ seed particles and organic particles as unity. Finally, the reviewer raised a good point that there may be variations in the electrical field strength of the chamber. During our routine experiments, we always ground the Teflon bags and maintain a constant relative humidity (40 %) in the chamber enclosure air. In addition, we perform the particle wall loss calibration experiments before and during the actual α -pinene + OH experiments to minimize the impact of variations in the electrical field on the particle deposition rates.

We have added the following clarification to emphasize that all growth curves have been particle wall loss corrected:

In section 4:

The upper bound is therefore less appropriate to use when vapor wall loss is accounted for separately, and thus the lower bound is used to correct the SOA data, using size-dependent wall loss rates measured in the Caltech chamber. Figure S2 shows temporal plots of the experimental non-particle wall loss corrected total volume and the total volume with both the upper and lower bound particle wall loss correction.

And additionally in section 5:

Experimental particle-wall-loss corrected SOA growth curves as a function of reacted α -pinene are shown in Fig. 2 for the six photooxidation experiments.

And in the caption of Figure 2:

Figure 2. Mass of SOA, MOA, as a function of reacted α -pinene. Experimental data are shown with filled circles, with colors corresponding to individual experiments (see Table 1), and have been corrected for particle wall loss (see text). Predictions using the default GECKO-A are shown as solid lines with the colors corresponding to the different experiments. In GECKO-A, the vapor-particle accommodation coefficient is set to $\alpha_p = 1$ and the vapor wall loss rate is set to $k_{gw} = 10^{-3} \text{ s}^{-1}$.

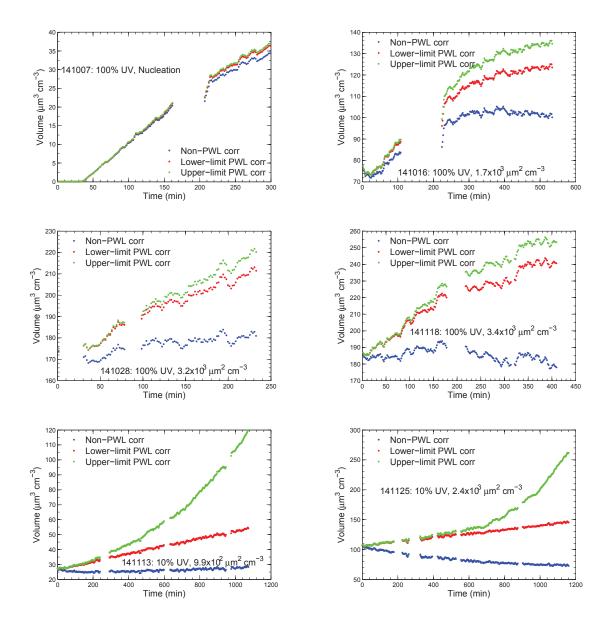


Figure S2: Caption on next page.

Figure S2: Total particle volume as a function of time, non-particle wall loss corrected (blue data points) and using two different corrections for particle wall loss. Red data points have been corrected with the lower bound assumption, in which deposited particles are assumed to not interact with vapor, and the mass of SOA present on a particle at the moment of its deposition is added to the total SOA. Green data points have been corrected with the upper bound assumption, in which deposited particles continue to grow via condensation at the same rate as suspended particles. The dramatic increase in the upper bound towards the end of the low UV experiments is likely an artifact of how the upper bound is calculated. The Aerosol Parameter Model (Pierce et al., 2008) is used to constrain the rate of condensation to particles by fitting the DMA size distribution at each time step, and this condensation rate is then applied to deposited particles. At the end of the low UV experiments, only 11% of the initial total number of particles remain suspended, as opposed to 30-40% for the high UV experiments. SOA growth in the α -pinene system is not seed surface area dependent (discussed in the Results section), and condensation to suspended particles will not decrease due to the decreased number. Therefore, at the end of the low UV experiments, the condensation rate per suspended particle is very large. With the upper bound correction, the deposited particles then grow with the same high condensation rate, despite the fact that transport to deposited particles will be slower than transport to suspended particles. The upper bound is likely a substantial overestimation for these experiments.

How was the particle number size distribution described in the model? Did you only consider one particle size or did you include several size bins? This should be mentioned in the article. If you only use one effective particle size bin how was the initial particle radius of the seed aerosol estimated?

The following explanation has been added to section 3.1:

In the model, a single particle size bin is used, so that all particles have the same radius. For all experiments except nucleation, the initial inorganic seed radius is set at 50 nm, and the initial number concentration is calculated from the measured initial seed surface area. GECKO-A does not currently include a mechanism for nucleation; therefore, for the nucleation experiment, an initial seed concentration of 10⁴ cm⁻³ was assumed with an initial radius of 5 nm.

On page 33173 L24-25 you write that the background levels of NO_x in the chemical model was set to 0.1 ppb and split evenly between NO and NO₂. I thought that you explicitly modeled the NO and NO₂ concentration. How were the inorganic gas-phase chemistry treated by the model?

The reviewer is correct that NO and NO₂ are explicitly simulated in the model. We meant to imply that the initial concentration of NO_x was split evenly between NO and NO_2 . The following clarification has been added to the paper:

Therefore, the initial background concentration in the simulations was set to 0.1 ppb, split evenly between NO and NO₂. NO and NO₂ then evolve throughout the simulation according to the standard inorganic gas-phase reactions.

On page 33178 L5-7 you write "A reduction to 10% and a wall loss rate of 10⁻⁵ s⁻¹ results in the best fit to both high and low UV experiments (Fig. 6), albeit with a slight overprediction for the high UV experiments and slight underprediction for the low UV experiments." I would not say that the model underprediction for experiment 141125 is a "slight" underprediction but a rather substantial underprediction of about 40 %. I suggest that instead of using the terms "slight overprediction" and "slight underprediction" give values of how much in % that the model over-and underpredicts the SOA mass in the end of the experiments.

We have revised this sentence as follows:

A reduction to 10% and a wall loss rate of 10⁻⁵ s⁻¹ results in the best fit to both high and low UV experiments (Fig. 5), albeit with an overprediction up to 75% for the high UV experiments and a 20-40% underprediction for the low UV experiments.

On page 33180, L4-10 you conclude that the underprediction of vapor pressure is likely not responsible for the enhanced contribution of later-generation species to SOA. I am not totally convinced about this. It might be correct but I don't think that you can base these conclusions only based on a comparison of different functional group contribution methods since they all have in common that they estimate the vapor pressures by summing up the contribution from different functional groups and in the best case take into account some interactions between the different functional groups. It might very well be that all these methods systematically underestimate (or overestimate) the vapor pressures of compounds with many functional groups.

We have revised this discussion to read:

While the Nannoolal et al. (2008) method generally led to the highest volatilites and the lowest SOA predictions when compared to the Myrdal and Yalkowsky (1997) method and the SIMPOL-1 method from Pankow and Asher (2008), each of these methods estimates vapor pressures via a group contribution method (i.e. summing the contributions of all functional groups). If this approach is less accurate for compounds with many functional groups, the volatilities may be underpredicted and these species may be overpredicted in SOA.

The difference in seed aerosol (SA) surface area (a proxy for the condensation sink) is not that great between the experiments called low SA, medium and high SA. Maybe you could give the value of the initial seed surface area in the figure legends instead of calling the experiments "Low SA", "Medium SA" and "High SA".

We have changed all legends to give the value of the initial seed surface area instead of using the labels "Low SA," "Medium SA", and "High SA."

For the nucleation experiment I think that one possible reason for the relatively high SOA yield is caused by substantially lower wall losses of these particles. This is because I suspect that the particles that are formed via new particle formation are under charged with respect to the Boltzmann charge distribution. I guess the SA was neutralized before it was introduced to the chamber. Thus I don't think it is appropriate to do the same wall loss correction for the nucleation experiment as for the SA experiments. Did you use different size resolved wall loss corrections for the SA experiments and the nucleation experiment?

No, we did not use different size-resolved wall loss corrections for the SA experiments and the nucleation experiment. The nucleation experiment was hardly affected by the particle wall loss correction (shown in Figure S2 previously). Because the particle wall loss correction affected the nucleation experiment so insignificantly, it is unlikely that this explains the high SOA yield in the nucleation experiment.

Technical correction:

The text is very small in Fig. 3 and hard to read. If Fig. 3 should be included in the final manuscript the font of the text needs to be larger. I personally thing that Fig. 3 can be removed from the manuscript because it adds very little to the article and you only refer to it once in the text.

We agree that Fig. 3 does not add significantly to the article, and we have removed it.

Added references:

Kurtén, T., Rissanen, M. P., Mackeprang, K., Thornton, J. A., Hyttinen, N., Jørgensen, S., Ehn, M., and Kjaergaard, H.G.: Computational study of hydrogen shifts and ring-opening mechanisms in α-pinene ozonolysis products, J. Phys. Chem. A., 119, 11366–11375, 2015.

Ma, Y., Russell, A. T., and Marston, G.: Mechanisms for the formation of secondary organic aerosol components from the gas-phase ozonolysis of α -pinene, Phys. Chem. Chem. Phys., 10, 4294–4312, 2008.

Tobias, H. J., and Ziemann, P. J.: Kinetics of the gas-phase reactions of alcohols, aldehydes, carboxylic acids, and water with the C13 stabilized Criegee intermediate formed from ozonolysis of 1-tetradecene, J. Phys. Chem. A., 105, 6129–6135, 2001.

Anonymous Referee #2

We thank the reviewer for the helpful comments. We respond to each comment below. Original comments are in **black**. Our responses are in blue, and changes/additions to the manuscript are in *italics*.

The McVay et al. manuscript reports on the alpha-pinene+OH oxidation mechanism and resultant SOA, investigated using comparative measurements and modeling. Smog chamber experiments were conducted under low NO (< 2 ppb) and low and high OH (2x105 and 2x106 molecules/cm3, respectively) conditions; modeling was performed using the GECKO-A model. The GECKO-A model was updated to include gas-phase chemistry based on Vereecken et al. (2007) and dynamic gas/particle partitioning based on La et al. (2015). The significant finding was that OH levels did not influence SOA growth in the chamber studies but did influence growth in the modeling studies. Explanations for the need of a higher vapor wall loss rate in GECKO-A to match the high UV/OH experiments were explored. It was concluded that GECKO-A overestimates the contribution of latergeneration (2nd and higher) species to SOA formation. The manuscript provides good insight into variability of vapor wall loss rates (e.g., in different chambers and in different chemical systems) and the potential for over contribution of later-generation oxidation products in GECKO-A. The manuscript is very well written and easy to follow. It is recommended that following attention to the minor comments provided, the manuscript be accepted for publication in ACP.

Minor comments: p. 33164, line 10: It is suggested that the authors consider adding "near" before explicit. It is my understanding that GECKO-A follows the Master Chemical Mechanism to the point at which the SARs are invoked, including as regards to the assumption that all understudied compounds and chemical reactions can be represented by a subset of studied reactions and similar compounds.

We have added "near" before explicit.

p. 33176, line 8: spelling "preferentially"

We thank the reviewer for catching this typo. It has been corrected.

Fig. 3: It is recommended to increase text size, particularly the high/low UV/OH and the explanation headers.

We agree that Fig. 3 is difficult to read, and we agree with Anonymous Reviewer #1 that this figure adds little to the article. Therefore, we have removed this figure.

Supplement, Fig. S3 discussion: The authors note that the remaining number concentration in the low UV/OH experiment is \sim 3x less than that of the high UV/OH experiment. Do the authors attribute this to size-dependent or compositionally-dependent wall losses of the particles?

We attribute this primarily to the much longer experiment time of the low UV experiments: these experiments were run for 18-20 h compared to 7-9 h for the high UV experiments. Over the longer time of the low UV experiments, more particles have time to deposit to the wall.

I agree with the first reviewer's comment that underestimation of vapor pressures for multi-functional (later-generation) oxidation compounds should not be ruled out.

We agree with both reviewers that underestimation of vapor pressures for multi-functional compounds should not have been ruled out. We have revised the manuscript to reflect this:

While the Nannoolal et al. (2008) method generally led to the highest volatilites and the lowest SOA predictions when compared to the Myrdal and Yalkowsky (1997) method and the SIMPOL-1 method from Pankow and Asher (2008), each of these methods estimates vapor pressures via a group contribution method (i.e. summing the contributions of all functional groups). If this approach is less accurate for compounds with many functional groups, the volatilities may be underpredicted and these species may be overpredicted in SOA. Manuscript prepared for Atmos. Chem. Phys. Discuss. with version 2015/04/24 7.83 Copernicus papers of the LATEX class copernicus.cls. Date: 17 February 2016

SOA formation from the photooxidation of α -pinene: systematic exploration of the simulation of chamber data

R. C. McVay¹, X. Zhang², B. Aumont³, R. Valorso³, M. Camredon³, Y. S. La³, P. O. Wennberg^{2,4}, and J. H. Seinfeld^{1,2}

¹Division of Chemistry and Chemical Engineering, California Institute of Technology, Pasadena, CA 91125, USA

²Division of Engineering and Applied Science, California Institute of Technology, Pasadena, CA 91125, USA

³LISA, UMR CNRS/INSU 7583, Université Paris Est Créteil et Université Paris Diderot, Institut Pierre Simon Laplace, 94010 Créteil CEDEX, France

⁴Division of Geological and Planetary Sciences, California Institute of Technology, Pasadena, CA 91125, USA

Correspondence to: J. Seinfeld (seinfeld@caltech.edu)

Discussion Paper

Abstract

Chemical mechanisms play an important role in simulating the atmospheric chemistry of volatile organic compound oxidation. Comparison of mechanism simulations with laboratory chamber data tests our level of understanding of the prevailing chemistry as well as the dynamic processes occurring in the chamber itself. α -pinene photooxidation is a well-studied system experimentally, for which detailed chemical mechanisms have been formulated. Here, we present the results of simulating low-NO α -pinene photooxidation experiments conducted in the Caltech chamber with the Generator for Explicit Chemistry and Kinetics of Organics in the Atmosphere (GECKO-A) under varying concentrations of seed particles and OH levels. Unexpectedly, experiments conducted at low and high OH levels yield the same SOA growth, whereas GECKO-A predicts greater SOA growth under high OH levels. SOA formation in the chamber is a result of a competition among the rates of gas-phase oxidation to low volatility products, wall deposition of these products, and condensation into the aerosol phase. Various processes, such as photolysis of condensed-phase products, particle-phase dimerization, and peroxy radical autoxidation, are explored to rationalize the observations. In order to explain the observed similar SOA growth under different OH levels, we conclude that vapor wall loss in the Caltech chamber is likely of order 10^{-5} s⁻¹, consistent with previous experimental measurements in that chamber. We find that GECKO-A tends to overpredict the contribution to SOA of later-generation oxidation products under high OH conditions. Moreover, we propose that autoxidation may alternatively resolve some or all of the measurement-model discrepancy, but this hypothesis cannot be confirmed until more explicit mechanisms are established for α -pinene autoxidation. The key role of the interplay among oxidation rate, product volatility, and vapor-wall deposition in chamber experiments is illustrated.

Discussion Paper

1 Introduction

Secondary organic aerosol (SOA) contributes substantially to the tropospheric particle mass loading (Jimenez et al., 2009), which in turns influences visibility, direct radiative forcing, cloud formation, and human health (Hallquist et al., 2009). Monoterpenes contribute significantly to global SOA formation with an estimated emission rate of $100-130 \,\mathrm{Tg}\,\mathrm{Cyr}^{-1}$ and SOA mass yield of 10-20% (Hoffmann et al., 1997; Pye et al., 2010; Guenther et al., 1995). Of the terpenes, α -pinene has the highest estimated emission rate of 34 Tg Cyr⁻¹ (Pye et al., 2010). Numerous studies have examined SOA formation from both the OH oxidation and ozonolysis of α -pinene (Hoffmann et al., 1997; Griffin et al., 1999; Kamens and Jaoui, 2001; Takekawa et al., 2003; Presto et al., 2005a, b; Ng et al., 2006; Pathak et al., 2007; Shilling et al., 2008; Ng et al., 2007a; Eddingsaas et al., 2012b). Ozonolysis is a more efficient route to α -pinene SOA than OH oxidation (Griffin et al., 1999), and the ozonolysis path has received considerable attention. Fewer studies have examined SOA formation from OH oxidation of α -pinene, and even fewer studies have focused on low-NO conditions, under which most α -pinene is oxidized (Nozière et al., 1999; Ng et al., 2007a; Claeys et al., 2009; Eddingsaas et al., 2012a). However, nearly half of the global sink of α -pinene has been estimated to be reaction with OH (42%); the remainder is oxidized predominantly by O_3 , with only 12% oxidized by NO_3 (Capouet et al., 2008).

As in virtually all volatile organic compound (VOC) systems that lead to SOA, the OH oxidation of α -pinene is complex, and parts of the mechanism are still not fully characterized (Peeters et al., 2001; Vereecken et al., 2007; Eddingsaas et al., 2012a, b). Theoretical and experimental work has indicated that heretofore unidentified alkoxy and peroxy isomerization channels may contribute substantially to SOA formation (Peeters et al., 2001; Capouet et al., 2004; Vereecken et al., 2007; Ehn et al., 2014; Rissanen et al., 2014). Further evidence suggests that particle-phase dimerization reactions are also important to SOA growth in the α -pinene system, although most studies have focused on the ozonolysis path (Gao et al., 2004a, b; Lopez-Hilfiker et al., 2015). Condensed-phase photolysis has also been shown to affect SOA formation from α -pinene, although again the focus has been predominantly on SOA produced via ozonolysis (Henry and Donahue, 2012; Donahue et al., 2012; Epstein et al., 2014; Wong et al., 2015). Uncertainty in the mechanism of SOA formation by photooxidation leads to uncertainty in global predictions of α -pinene SOA (Pye et al., 2010).

Experiments in environmental chambers produce the basic data on the extent of SOA formation from volatile organic compounds and provide a means to test our understanding of the underlying chemistry of SOA formation. Simulations with explicit chemical mechanisms provide a means to evaluate predictions of SOA formation using chamber observations made under a variety of conditions (Capouet et al., 2008; Valorso et al., 2011). The goal of the present work is to carry out such an evaluation for the α -pinene OH photooxidation system.

2 α -pinene photooxidation mechanism

2.1 Gas-phase OH oxidation

An explicit A near-explicit gas-phase oxidation mechanism for the oxidation of α -pinene was generated using the Generator for Explicit Chemistry and Kinetics of Organics in the Atmosphere (GECKO-A) (Aumont et al., 2005; Camredon et al., 2007). GECKO-A automatically assigns reactions and rate constants on the basis of experimental data and Structure-Activity Relationships (SARs), producing chemical mechanisms far more detailed and explicit than can be written manually (Aumont et al., 2005). As described in Valorso et al. (2011), a protocol is implemented in GECKO-A to reduce the number of species generated to meet computational limits while maintaining as much chemical detail as possible; for example, gas-phase chemistry is not generated for species with vapor pressures below 10^{-13} atm and isomer substitution is allowed for position isomers for non-radical species formed with a maximum yield less than 2% after two or more generations. Vapor pressures are estimated using the Nannoolal et al. (2008) method. Four generations of OH-oxidation of α -pinene in GECKO-A (a generation encompassing reaction with an oxidant such as OH

up to the formation of a stable product) yield 9×10^5 reactions and 1.8×10^5 species. SOA predictions for the base case are found not to be sensitive to the number of generations beyond three (sensitivity tests not shown).

OH oxidation of α -pinene proceeds predominantly via OH addition, with minor channels proceeding via hydrogen abstraction. An overview of the base mechanism in GECKO-A for the OH oxidation of α -pinene is shown in black in Fig. 1 and discussed in more detail in Valorso et al. (2011). Updates to this mechanism (shown in blue in Fig. 1) were added here based on recent literature. Vereecken et al. (2007) proposed several non-traditional pathways in the OH oxidation of α -pinene based on guantum- and theoretical chemical calculations. Species in Fig. 1 are labeled to be consistent with Vereecken et al. (2007). Species R1 is formed with 22% yield by a prompt ring-opening of the four-membered ring following initial OH addition to the double bond in α -pinene (Peeters et al., 2001). A 40:60 ratio of syn vs. anti stereochemistry is estimated for species R1 (Vereecken et al., 2007). The *anti* conformer is predicted to undergo a 1,6-hydrogen shift to form a peroxide, forming a radical stabilized by allyl resonance, R7. This reaction is predicted to dominate over all other peroxy reactions for the anti conformer even in high-NO conditions. The position of oxygen addition to the alkyl radical R7 is not well-constrained. The branching ratio between addition at the secondary and tertiary sites has conservatively been predicted to be 50:50 (Vereecken et al., 2007). Vereecken et al. (2007) calculate that the syn conformer of R1 will participate in traditional peroxy chemistry but will also undergo ring closure to form a six-membered ring, species R3. Vereecken et al. (2007) calculate a rate constant for this reaction of 2.6 s⁻¹ at 298 K. Species R2 in Fig. 1, formed from the reaction of the syn conformer of species R1 with NO and RO₂, is predicted to undergo a ring-closure reaction to form species R10. This reaction is predicted to dominate over acetone elimination and hydroxy formation, the previous pathways for R2 in GECKO-A (Valorso et al., 2011). R10 adds oxygen and then participates in the usual peroxy reactions.

The HO₂ chemistry has also been updated in GECKO-A. The main reaction channel for reaction of alkyl peroxy radicals with HO₂ is formation of hydroperoxides. Recent evidence indicates that the reaction of some peroxy radicals with HO₂ can also lead to an alkoxy

radical, regenerating OH (Hasson et al., 2004; Dillon and Crowley, 2008; Birdsall et al., 2010; Eddingsaas et al., 2012a). This reaction is promoted by the presence of neighboring polar functional groups, which can stabilize the intermediate leading to the alkoxy through hydrogen bonding (Hasson et al., 2005). This pathway has been added to GECKO-A for molecules with an oxygenated moiety in the α position to the peroxy radical. Estimates of the yield of the alkoxy for small acyl peroxy radicals range from 0.15–0.7 (Hasson et al., 2004; Dillon and Crowley, 2008); however, branching ratios for the larger molecules in the α -pinene mechanism have not been determined. In light of this uncertainty, the branching ratio between the hydroperoxide and the alkoxy has been assigned to 80:20 in GECKO-A.

Ozonolysis chemistry in GECKO-A does not explicitly include the Criegee biradicals formed from the addition of O_3 to the α -pinene double bond; rather the predicted products of the Criegee intermediates are directly assigned to the α -pinene ozonolysis reaction. This simplification overlooks potential reactions of the stabilized Criegee intermediates (SCI) with water, alcohols, acids, carbonyls, etc. (Ma et al., 2008; Tobias and Ziemann, 2001). Reaction of the SCI with water to form pinonaldehyde is thought to be significant (Capouet et al., 2008), and a direct route to pinonaldehyde has been added in GECKO-A. The initial reaction step for ozonolysis is shown in Fig. S1. Furthermore, Ma et al. (2008) proposed several later-generation intramolecular isomerization reactions to form low-volatility acids. These reactions have been implemented in GECKO-A as a sensitivity test. Virtually no change in predicted SOA concentrations is observed when adding these reactions or when changing the branching ratios of the SCI products. Separate (not shown) purely ozonolysis simulations showed very little SOA formation, indicating potential missing pathways in the ozonolysis mechanism forming low-volatility products. Updating the ozonolysis mechanism should be the subject of future studies. The above updates constitute the base mechanism. Sensitivity tests applied on this base mechanism are addressed in the sections that follow.

2.2 Condensed-phase photolysis

Photolysis of gas-phase compounds containing carbonyl, peroxide or nitrate chromophores is included automatically within oxidation schemes generated by GECKO-A (Aumont et al., 2005). For the simulations presented here, compound-specific photolysis rates are calculated using cross sections and quantum yields described in Aumont et al. (2005) and measured irradiance data in the Caltech chamber. Photolysis of condensed-phase compounds, recently shown to lead to rapid loss of α -pinene SOA (Henry and Donahue, 2012; Donahue et al., 2012; Epstein et al., 2014; Wong et al., 2015), is included here as a possible reaction route. Because GECKO-A does not generate chemical reactions within the condensed phase, radical species produced by condensed-phase photolytic reactions are assumed to be irreversibly lost and to not participate in subsequent chemistry (Hodzic et al., 2015). This approximation likely represents an upper limit to the actual physical process since it does not account for recombination of fragments in the particle phase (Henry and Donahue, 2012; Hodzic et al., 2015). Two methods of calculating condensed-phase photolysis rate constants were tested in Hodzic et al. (2015): (1) all photolabile compounds in the condensed phase are assigned the same empirically-derived rate constant, and (2) the condensed-phase photolytic rate constant for each species is set to the corresponding gas-phase value. Hodzic et al. (2015) showed that the second method generally results in a greater loss of SOA. Therefore, assumption (2) is tested in the present simulations to evaluate the maximum possible impact of condensed-phase photolysis on overall SOA growth.

2.3 Particle-phase dimerization

The importance of aerosol-phase dimerization and oligomerization reactions has been demonstrated (Kalberer et al., 2004; Gao et al., 2004a, b; Tolocka et al., 2004; Yee et al., 2013; Shiraiwa et al., 2013; Fahnestock et al., 2014). These include alcohol + carbonyl to form hemiacetals and acetals, hydroperoxide + carbonyl to form peroxyhemiacetals and peroxyacetals, carboxylic acid + alcohol to form esters, and aldehyde self-reactions to form

aldols (Ziemann and Atkinson, 2012). Shiraiwa et al. (2013) modeled a generalized particlephase reaction of an SVOC + carbonyl with a rate constant of $12 \,\text{M}^{-1} \,\text{s}^{-1}$ when fitting the observed evolution of the particle size distribution of dodecane SOA. In contrast, Capouet et al. (2008) modeled the formation of peroxyhemiacetals during α -pinene SOA formation using a rate constant of $0.06 \,\text{M}^{-1} \,\text{s}^{-1}$; they found that these reactions had a minor impact on SOA yield, except during ozonolysis with large VOC/NO_x ratios that led to high hydroperoxide yields.

In the present work, particle-phase dimerization reactions have been added to the GECKO-A α -pinene oxidation scheme for aldehydes, hydroperoxides, alcohols, and carboxylic acids. Three reaction pairings are considered: aldehyde + alcohol, aldehyde + hydroperoxide, and carboxylic acid + alcohol. As a first approximation, reactions are assumed to be irreversible and to form nonvolatile products. The mass of dimers becomes part of the organic aerosol mass into which gas-phase species can partition. The rate constant is set to be the same for each dimerization reaction and two values are tested: $12 \text{ M}^{-1} \text{ s}^{-1}$ (Shiraiwa et al., 2013) and $0.01 \text{ M}^{-1} \text{ s}^{-1}$ (Ziemann and Atkinson, 2012). The rate constant is converted from liters of solution to volume of chamber air based on the amount of organic aerosol condensed at each time step.

3 Box model for SOA formation

Each α -pinene oxidation scheme generated for the different sensitivity tests is coupled to a box model describing the chemical dynamics within the chamber, including dynamic transport of vapors to the particle phase and to the chamber walls.

3.1 Vapor-particle transport

In previous versions of GECKO-A, instantaneous equilibrium partitioning is assumed to occur between the vapor and particle phases (Camredon et al., 2007; Lee-Taylor et al., 2015). As a more general treatment of vapor-particle transport, dynamic partitioning for mass transfer between the gas and the particle phase is implemented here as described

Discussion Paper

in ? La et al. (2016), with a few modifications. Mass transfer to and from the particle is represented by

$$\left(\frac{\mathrm{d}G_i}{\mathrm{d}t}\right)_{\rm gp} = -k_{\rm gp}G_i + k_{\rm pg}P_i$$

$$\left(\frac{\mathrm{d}P_i}{\mathrm{d}t}\right)_{\rm pg} = k_{\rm gp}G_i - k_{\rm pg}P_i$$

$$(1)$$

where k_{gp} and k_{pg} are first-order rate constants for transport to and from the particle (s⁻¹), and G_i and P_i are concentrations in the gas and particle phase, respectively. Mass transfer can be limited by either gas-phase diffusion, interfacial accommodation, or particle-phase diffusion (e.g., Mai et al., 2015). Particle-phase diffusion in GECKO-A is assumed to be sufficiently rapid that particles are well-mixed. Recent studies have shown that the assumption of rapid particle-phase diffusion in SOA may not be accurate owing to semi-solid behavior (Perraud et al., 2012; Cappa and Wilson, 2011; Vaden et al., 2010, 2013; Virtanen et al., 2010, 2011; Kuwata and Martin, 2012; Saukko et al., 2012; Abramson et al., 2013; Renbaum-Wolff et al., 2013). Computationally, the gas-particle accommodation coefficient, α_p , is used to approximate resistances to gas-particle partitioning from surface accommodation and particle-phase diffusion (Saleh et al., 2013). Therefore, the overall rate constant of mass transfer k_{gp} can be approximated as

$$\frac{1}{k_{\rm gp}} = \frac{1}{k_{\rm diff}} + \frac{1}{k_{\rm int}} \tag{3}$$

with $k_{\text{diff}} = 4\pi D_{\text{g}} r_{\text{p}} C_{\text{p}}$ and $k_{\text{int}} = \alpha_{\text{p}} \bar{c} \pi r_{\text{p}}^2 C_{\text{p}}$, where D_{g} is the species gas-phase diffusivity, r_{p} is the particle radius, C_{p} is the number of particles per unit volume of air, α_{p} is the gas-particle accommodation coefficient, and \bar{c} is the gas-phase mean velocity (Seinfeld and Pandis, 2006). In the present work, the accommodation coefficient α_{p} is treated as a parameter that can be varied in order to produce the best fit to the observed SOA growth. In the model, the a single particle size bin is used, so that all particles have the same radius. For all experiments except nucleation, the initial inorganic seed radius is set at 50 nm, and the initial number concentration is calculated from the measured initial seed surface area. GECKO-A does not currently include a mechanism for nucleation; therefore, for the nucleation experiment, an initial seed concentration of 10^4 cm^{-3} was assumed with an initial radius of 5 nm. The number concentration of particles C_p in the model remains unchanged over the course of the experiment as r_p grows owing to condensation of organic aerosol. Particle wall loss is not included in the modelGECKO-A. SOA growth in the α -pinene system is essentially independent of seed surface area (discussed in the Results section); therefore, lack of particle wall loss in GECKO-A will not substantially affect SOA predictions. GECKO-A does not currently include a mechanism for nucleation; therefore, for the nucleation experiment, an initial seed concentration of 10^4 cm^{-3} was assumed with an initial radius of 5nm. r_p is calculated at each time step as

$$r_{\rm p} = \left(\frac{3}{4\pi} \left(\frac{4}{3}\pi r_{\rm p0}^3 + \frac{M_{\rm aer}C_{\rm aer}}{N_A\rho_{\rm OA}C_{\rm p}}\right)\right)^{\frac{1}{3}} \tag{4}$$

where r_{p0} is in the initial inorganic seed radius, M_{aer} is the organic aerosol mean molecular weight, C_{aer} is the organic aerosol mass concentration (molec cm⁻³), and ρ_{OA} is the organic aerosol density (1.32 g cm⁻³ for α -pinene SOA (Ng et al., 2007a)). Condensation to and evaporation from the particle occurs until equilibrium is reached between the gas and particle phases (if ever). The gas-particle partitioning at equilibrium is assumed to follow Raoult's law; therefore the reverse rate constant for mass transfer from the particle to the gas-phase is calculated from the relationship (?)-(La et al., 2016)

$$\frac{k_{\rm gp}}{k_{\rm pg}} = \frac{RT}{P^{\rm vap}} \frac{C_{\rm aer}}{M_{\rm aer}\gamma_{\rm aer}}$$
(5)

where R is the ideal gas constant, T is the temperature, P^{vap} is the species vapor pressure, and γ_{aer} is the activity coefficient in the particle phase (assumed to be 1).

Discussion Paper

3.2 Vapor-wall transport

Chamber data are affected by wall deposition of semi and low-volatility vapors (Loza et al., 2010; Matsunaga and Ziemann, 2010; Kokkola et al., 2014; Yeh and Ziemann, 2014, 2015; Zhang et al., 2014, 2015; Bian et al., 2015). Partitioning of vapor species between the gas phase and the chamber wall is based on the parameterization of Matsunaga and Ziemann (2010) and is implemented as described in ?-La et al. (2016), with minor variations. Reported values for the rate of transport from the gas to the wall, k_{qw} , span several orders of magnitude in different chambers (Matsunaga and Ziemann, 2010; Zhang et al., 2014, 2015; Loza et al., 2010, 2014). Wall loss rates directly measured in the Caltech chamber are of order 10^{-5} – 10^{-6} s⁻¹ (Zhang et al., 2015; Loza et al., 2010, 2014), although Zhang et al. (2014) fit a wall loss rate of 10^{-4} s⁻¹ during toluene SOA experiments. Gas-wall equilibration timescales, $\tau_{g,w}$, of order 10–100 min have consistently been measured in the 8.2 m³ chamber used by Yeh and Ziemann (2015). With $\tau_{a,w} = 1/(k_{aw} + k_{wa})$ (?) (La et al., 2016), these timescales correspond to wall loss rates of 10^{-3} – 10^{-4} s⁻¹. The Yeh and Ziemann (2015) chamber is smaller than the Caltech chamber, 8.2 vs. 24 m³; however, the differences in measured wall loss rates are greater than expected if wall loss scales with the surface-to-volume ratio of the chamber. It has been suggested that rapid initial vapor wall loss could be difficult to distinguish from changes in concentration due to injection and mixing during the long fill period in the Caltech chamber (Zhang et al., 2014; Loza et al., 2014). Vapor species could potentially rapidly equilibrate with the wall and be subsequently lost to the wall with a much slower uptake owing to relaxation of the Teflon polymer (Yeh and Ziemann, 2015). Sensitivity tests in the present work examine the extent to which these differences indicate significantly slower vapor wall loss in the Caltech chamber or arise from the procedure by which experimental measurements were carried out. Furthermore, Zhang et al. (2015) showed that k_{aw} may depend on the species' volatility; here we assume k_{aw} to be the same for all species in order to evaluate the order of magnitude of k_{aw} needed to fit the observations. The nominal value is set to 10^{-3} s⁻¹. As an additional sensitivity test, we implement the k_{ow} parameterization developed by Zhang et al. (2015) in which k_{ow}

Discussion Paper

increases as species' volatility decreases. Transport between the gas-phase and the wall is represented by the balance equations,

$$\left(\frac{\mathrm{d}G_i}{\mathrm{d}t}\right)_{\mathrm{gw}} = -k_{\mathrm{gw}}G_i + k_{\mathrm{wg}}W_i \tag{6}$$

$$\left(\frac{\mathrm{d}W_i}{\mathrm{d}t}\right)_{\mathrm{wg}} = k_{\mathrm{gw}}G_i - k_{\mathrm{wg}}W_i \tag{7}$$

where k_{aw} and k_{wq} are first-order rate constants for transport to and from the wall, and W_i is the concentration in the wall layer. The reverse rate is calculated assuming gas-wall partitioning follows Raoult's law (?) (La et al., 2016) :

$$\frac{k_{\rm gw}}{k_{\rm wg}} = \frac{RT}{P^{\rm vap}} \frac{C_{\rm w}}{M_{\rm w} \gamma_{\rm w}} \tag{8}$$

where $C_{\rm w}$ is the equivalent overall organic mass concentration in the wall, $M_{\rm w}$ is the equivalent molar weight of the organic concentration in the wall, and γ_w is the activity coefficient in the Teflon film. Values of $C_w/M_w\gamma_w$ must be determined experimentally from chamber observations (Matsunaga and Ziemann, 2010; Zhang et al., 2015). In the present simulations, a nominal $C_w/M_w\gamma_w$ value of 120 µmol m⁻³, the value determined by Matsunaga and Ziemann (2010) for 2-ketones, is used for all species except for α -pinene, for which $C_{\rm w}/M_{\rm w}\gamma_{\rm w} = 20\,\mu{\rm mol\,m^{-3}}$, the value determined by Matsunaga and Ziemann (2010) for alkenes. $C_w/M_w\gamma_w$ is varied as a sensitivity test.

Experimental 4

Six α -pinene photooxidation experiments were conducted in the Caltech dual 24 m³ environmental chambers at ~ 298 K and < 5% RH (Table 1). Prior to each experiment, the Teflon chambers were flushed with purified, dry air for 24 h until the particle number concentration was $< 10 \,\mathrm{cm}^{-3}$ and volume concentration was $< 0.01 \,\mathrm{\mu m}^3 \,\mathrm{cm}^{-3}$. Hydrogen peroxide (H₂O₂) was used as the OH source by evaporating 113 µL of 50 wt% aqueous solution into the chamber with 5 L min⁻¹ purified air for 110 min, resulting in an approximate starting H₂O₂ mixing ratio of 2 ppm. Experiments were conducted at low NO (< 2 ppb). Heated 5L min⁻¹ of purified, dry air flowed through the glass bulb was flowed through a glass bulb containing liquid α -pinene into the chamber for 30 min, introducing ~ 50 ppb α -pinene into the chamber. Ammonium sulfate (AS) seed aerosol was injected into the chamber by atomizing 0.015 or 0.1 M aqueous (NH₄)₂SO₄ solution into the chamber for 30 to 90 min, varying the initial AS concentration in order to vary the seed surface area (SA) available for condensation. After ~ 1h mixing, photooxidation was initiated. Four of the experiments were performed using the full set of blacklights, for which the calculated $j_{NO_2} = 4 \times 10^{-3} s^{-1}$, with varying amounts of inorganic seed particles (Table 1). The remaining two experiments were performed using only 10% of the available blacklights, for which the calculated $j_{NO_2} = 3.7 \times 10^{-4} s^{-1}$, again with varying amounts of inorganic seed particles.

Relative Humidity (RH) and temperature were monitored via a Vaisala HMM211 probe. O₃ and NO_x mixing ratios were measured by a Horiba O₃ analyzer (APOA-360) and a Teledyne NO_x analyzer (T200), respectively. α -pinene concentration was monitored by a gas chromatograph equipped with a HP-5 column ($15 \text{ m} \times 0.53 \text{ mm}$ ID $\times 1.5 \mu \text{ m}$ thickness, Hewlett-Packard) coupled with flame ionization detector (GC/FID, Agilent 6890N). The size distribution and number concentration of seed particles and organic aerosols were characterized using a custom-built Scanning Mobility Particle Sizer (SMPS) consisting of a Differential Mobility Analyzer (DMA, TSI, 3081) coupled with a Condensation Particle Counter (CPC, TSI, 3010).

Volume distributions are Measured volume distributions must be corrected for particle wall lossusing size-dependent wall lossrates measured in the Caltech chamber; the DMA measures the total volume of particles, which is a mixture of organic aerosol and inorganic seed. By accounting for particle wall loss, the seed volume can be subtracted and the mass of SOA calculated. Two limiting assumptions have traditionally been made when correcting for particle wall loss (?) (Loza et al., 2014) : In the lower bound, once deposited, particles

are assumed to no longer interact with the vapor. The mass of SOA present on a particle at the moment of its deposition is added when calculating the total SOA. In the upper bound, deposited particles are assumed to continue growing at the same rate as suspended particles, and this SOA is similarly added to the total SOA. The upper bound can be viewed as an early approximation of vapor wall loss from a time when vapor wall loss was less well understood. However, this approximation does not account for the differing mechanisms of vapor-particle and vapor-wall transport, which is reflected in different time scales. Moreover, the absorbing mass of the wall, represented by the parameter $C_{\rm w}$, is ~ 3 orders of magnitude higher than the mass of deposited particles (Zhang et al., 2014). The upper bound is therefore less appropriate to use when vapor wall loss is accounted for separately, and thus the lower bound is used here. The upper bound is shown for reference in Fig. S3 in the Supplement to correct the SOA data, using size-dependent wall loss rates measured in the Caltech chamber. Figure S2 shows temporal plots of the experimental non-particle wall loss corrected total volume and the total volume with both the upper and lower bound particle wall loss correction. (Gaps in the volume data resulted when the DMA was taken off line briefly to clean the inlet.)

The initial concentrations of H₂O₂, NO_x, and O₃ in the chemical model were optimized to match the α -pinene decay and O₃ formation. The initial mixing ratio of H₂O₂ was optimized to be 2 ppm, yielding predicted OH levels of ~ 2 × 10⁶ molec cm⁻³ for the 100% UV experiments and ~ 2 × 10⁵ molec cm⁻³ for the 10% UV experiments. Although experiments were conducted at low-NO conditions, background levels of NO_x were observed in the chamber. Due to voltage interference in the NO_x measurements at such low values, it was not possible to determine the exact amount of NO_x present in the chamber. Therefore, the background level in the chemical model initial background concentration in the simulations was set to 0.1 ppb, split evently evenly between NO and NO₂. NO and NO₂ then evolve throughout the simulation according to the standard inorganic gas-phase reactions. Ozone formation was observed during the experiments, giving evidence of the presence of NO₂ in the chamber. Because any NO₂ initially present in the chamber is quickly photolyzed, a NO_x wall off-gassing rate of 2.5 ppt min⁻¹ is needed to match the observed ozone forma-

tion (e.g., Valorso et al., 2011). Predicted SOA formation is not sensitive to the assumed NO_x off-gassing rate. An initial O₃ concentration was measured in the chamber; however, this was attributed to interference by H₂O₂ because α -pinene did not decay in the dark, as would have occurred in the presence of O₃. Therefore, the initial O₃ was set to zero in the model. Comparisons of measurements and model predictions for the decay of α -pinene and the evolution of O₃ are shown in Figs. S1 and S2 S3 and S4 in the Supplement.

Figure S5 shows the amount of α -pinene predicted to react with OH vs. O₃, using both the modeled and measured O₃ concentration. For the 100% UV experiments, ~2-3% of the total α -pinene is predicted to react with O₃, using either the modeled or measured O₃ concentration. For the 10% UV experiments, ~20% of the total α -pinene is predicted to react with O₃ using the modeled O₃ concentration. For experiment 141113, roughly the same amount of α -pinene is predicted to react with O₃ based on the measured O₃ concentration. However, for experiment 141125, because the model underpredicts the O₃ concentration, much more α -pinene is predicted to react with the measured O₃ concentration, ~49%.

5 Results

Observed Experimental particle-wall-loss corrected SOA growth curves as a function of reacted α -pinene are shown in Fig. 2 for the six photooxidation experiments. Corresponding temporal plots of SOA are shown in Fig. S3. (Gaps in SOA data resulted when the DMA was taken off line briefly to clean the inlet.) With the exception of the nucleation experiment, SOA growth is observed immediately upon irradiation, similar to Ng et al. (2007a). When presented as a function of reacted α -pinene, the growth curves essentially overlap, regardless of the UV level or the initial seed particle concentration. Overlap at two different UV intensities indicates that SOA growth is not very sensitive to the oxidation rate for these conditions. SOA yields (ratio of maximum mass of SOA formed to mass of α -pinene reacted) for these experiments range from 17 to 26 %, at the low end of the range of previously reported yields of 26–45% for this system (Ng et al., 2007a; Eddingsaas et al., 2012b).

Figure 2 also shows predictions from the base GECKO-A mechanism for the six experiments. In the GECKO-A model, the two main parameters representing vapor-particle and vapor-wall transport, α_p and k_{gw} , are set to nominal values of 1 and 10^{-3} s⁻¹, respectively. $C_{\rm w}/(M_{\rm w}\gamma_{\rm w})$ is set to 120 µmol m⁻³ for all species except α -pinene. These parameters give a good agreement for the 100% UV experiments. Figure S4-S6 in the Supplement shows the effect of varying the vapor-particle accommodation coefficient α_p for different values of the vapor wall loss rate k_{qw} . $\alpha_p = 1$ or 0.1 yield almost identical SOA predictions for all experiments except nucleation. In the nucleation case, $\alpha_{\rm p} = 0.1$ results in substantially less SOA predicted, which may result because nucleation is not treated explicitly in GECKO-A but instead approximated by initializing the particle concentration with particles of 5 nm radius. Lowering the value of $\alpha_{\rm p}$ to 0.01 or 0.001 delays the onset of SOA formation for the 100% UV experiments, which is not consistent with experimental observations. Lowering k_{aw} results in substantial overprediction of SOA for the 100% UV experiments. For the 10% UV experiments, all combinations of parameters underpredict the SOA. Figure S5 S7 in the Supplement shows the effect of varying $C_w/(M_w\gamma_w)$ for different values of the vapor wall loss rate k_{gw} . $C_w/(M_w\gamma_w)$ controls partitioning between the gas phase and the wall at equilibrium; therefore, variations in $C_w/(M_w\gamma_w)$ have more of an effect on SOA predictions when using a faster wall loss rate because equilibrium is approached sooner. The base $C_w/(M_w\gamma_w)$ and $k_{aw} = 10^{-3} \text{ s}^{-1}$ give the best agreement for 100 % UV experiments; however, SOA for the 10% UV experiments is still underpredicted. This discrepancy will be addressed subsequently. All subsequent simulations are conducted with $\alpha_{p} = 1$ and the base $C_w/(M_w\gamma_w)$.

The best-fit $\alpha_p = 1$ (and 0.1 for all experiments except nucleation) for the 100 % UV experiments suggests that there are no substantial limitations to vapor-particle mass transfer (Mai et al., 2015). This conclusion is consistent with the experimental observation that the SOA growth in this system is virtually independent of the amount of seed surface area present; dependence of SOA growth on seed surface area occurs only with diffusion- or

accommodation-limited vapor-particle mass transfer (McVay et al., 2014). Optimal $\alpha_p = 1$ or 0.1 is consistent with Saleh et al. (2013) who determined accommodation coefficients of order 0.1 for α -pinene ozonolysis SOA. This result differs from that of Zhang et al. (2014), who observed toluene SOA formation to depend strongly on the seed surface area and consequently to adhere to a low $\alpha_p = 0.001$. The different behavior observed for α -pinene and toluene SOA may reflect differences in SOA formation mechanisms; however, it is not possible to discern the reason for the difference based solely on the data at hand. If α -pinene SOA behaves as a semi-solid (Perraud et al., 2012; Cappa and Wilson, 2011; Vaden et al., 2010, 2013; Virtanen et al., 2010, 2011; Kuwata and Martin, 2012; Saukko et al., 2012; Abramson et al., 2013; Renbaum-Wolff et al., 2013), a lower α_p might be expected. However, if, once formed, SOA is converted into a glassy state through hydrogen bonding or oligomerization (Cappa and Wilson, 2011), SOA formation itself could still be characterized by a high α_p .

The observation that SOA growth is insensitive to oxidation rate (shown by the overlap of the growth curves in Fig. 2 for different UV exposures) is not consistent with predictions regarding the interplay of reaction rate and vapor wall loss: if the reaction rate increases relative to the vapor wall loss rate, successive generations of low volatility species will be produced more quickly and will condense prefernitially preferentially onto particles before their precursors are lost to the chamber walls, leading to a higher SOA yield (Zhang et al., 2014; McVay et al., 2014). Such behavior was observed experimentally by Ng et al. (2007b): higher SOA yields were observed in the aromatic system using HONO as an OH precursor than during those in which only NO and NO₂ are present initially, leading to much lower OH levels. This "rate effect" was tentatively attributed by Ng et al. (2007b) to loss of semivolatile organics to the chamber walls, although at a time when the nature of vapor wall deposition was less well understood. A dependence of SOA growth on oxidation rate is also predicted by the base scenario in GECKO-A: the SOA levels are predicted to be substantially lower at 10% UV owing to significant organic mass loss to the walls. A number of explanations can be advanced for the overlap of the growth curves at high and low UV . These possibilities are illustrated schematically in Fig. ?? and and these are systematically explored below.

Discussion Paper

5.1 Negligible or slow vapor wall loss

In the absence of vapor wall loss, the growth curves predicted by GECKO-A overlap at high and low UV (Fig. <u>S6 S8</u> in the Supplement). Oxidation occurs more slowly under low UV owing to the decreased rate of generation of OH, but if condensable species or their precursors do not deposit on the walls, the same amount of SOA eventually forms. However, in the absence of vapor wall loss, GECKO-A overpredicts SOA substantially for the high UV experiments and slightly for the low UV experiments.

At a low level of vapor wall loss, $k_{gw} = 10^{-5} s^{-1}$, the growth curves predicted by GECKO-A still essentially overlap (Fig. 3). A "rate effect", in which the SOA yield depends on the rate of oxidation, is observed only if the rate of oxidation is slower than or competitive with other loss processes. The rate constant for the reaction of OH with α -pinene is $5.23 \times 10^{-11} \text{ cm}^3 \text{ molec}^{-1} \text{ s}^{-1}$ (Atkinson and Arey, 2003). OH concentrations predicted by GECKO-A of 2×10^6 and 2×10^5 molec cm⁻³ for the high and low UV experiments, respectively, give overall reaction rates of 10^{-4} and 10^{-5} s^{-1} . (OH reaction rate constants for oxidized products will be slower than that for α -pinene, and the reaction rate slows in later generations). A vapor wall loss characterized by $k_{gw} = 10^{-3} \text{ s}^{-1}$ exceeds substantially either of these reaction rates, and thus at this wall deposition rate the effect of changing oxidation rate is strong. At a much slower wall loss, $k_{gw} = 10^{-5} \text{ s}^{-1}$, the rate effect is less pronounced, leading to overlap of the growth curves predicted by GECKO-A. The absence of a rate effect in the experimental observations is consistent with a slower vapor wall loss rate, in accord with wall loss rates that have been measured previously in the Caltech chamber (Loza et al., 2010, 2014; Zhang et al., 2015).

With a vapor wall loss rate of 10^{-5} s⁻¹, SOA predictions match the data fairly well at low UV, within $10 \,\mu g \,m^{-3}$ of the final SOA concentration, but remain overpredicted by 80 to $200 \,\mu g \,m^{-3}$ at high UV. Thus, a slow wall loss rate alone is not sufficient to reconcile the predictions at high and low UV. However, it is instructive to examine the contribution of different generations of reaction to SOA predictions with this slow vapor wall loss (Fig. 4). GECKO-A predicts that SOA will consist of almost entirely second-generation products. At the end of the experiment, simulations under high UV predict $\sim 100 \,\mu g \, m^{-3}$ of second-generation products, as opposed to $\sim 50 \,\mu g \, m^{-3}$ for low UV. Thus, reducing the contribution of second-generation products in high UV may result in closer model–data agreement for both high and low UV conditions at a slow vapor wall loss rate.

5.2 Overcontribution of second and later generation species

As a sensitivity test, all OH reaction rate constants, except that of OH + α -pinene, were are reduced by varying factors. Figure S7–S9 in the Supplement shows the impact of reducing the OH rate constants to 1, 10, and 50% of the default values at a vapor wall loss rate of $10^{-5} s^{-1}$. A reduction to 10% and a wall loss rate of $10^{-5} s^{-1}$ results in the best fit to both high and low UV experiments (Fig. 5), albeit with a slight overprediction an overprediction up to 75% for the high UV experiments and slight a 20-40% underprediction for the low UV experiments. While this result does not necessarily suggest that reaction rate constants in GECKO-A are overpredicted by an order of magnitude, it does suggest that second and higher-generation compounds may be primarily responsible for the model–measurement discrepancy at differing UV levels. An excess contribution of later-generation compounds to SOA in GECKO-A could be due to several factors: (1) overprediction of the OH reaction rate constants by the SARs, (2) assumed reaction pathways in GECKO-A, (3) underestimation of volatilities for later-generation species, or (4) significantly faster wall loss rate for later generation products. Each of these possibilities is considered in turn.

OH reaction rate constants in GECKO-A are based on SARs from Kwok and Atkinson (1995) and subsequent updates, which have been shown to predict OH reaction rate constants within a factor of 2 for alkanes, alkenes, and diols, but may be more uncertain for the complex and highly functionalized compounds in later generations of α -pinene oxidation (Bethel et al., 2001). For example, Bethel et al. (2001) showed that OH rate constants for 1,2-hydroxyaldehydes are overestimated by factors of 3–4 using the established SARs. Although rate constants are likely not overpredicted by an order of magnitude as the simulations suggest, it is possible that uncertainties in the SARs for later-generation species may contribute to the overprediction of these products by GECKO-A.

SARs used to predict reaction pathways and branching ratios in GECKO-A are also prone to uncertainties. In the reaction of peroxy radicals with HO₂, the dominant pathway in GECKO-A is formation of the hydroperoxide (assumed branching ratio 80 %). α -pinene hydroxy dihydroperoxide (C₁₀H₁₆O₅) is a second-generation compound formed via two such reactions with HO₂ that is predicted by GECKO-A to contribute significantly to SOA at the high UV conditions. Figure S8-S10 in the Supplement shows that eliminating the mass of this compound from SOA predictions in the absence of vapor wall loss results in a much more significant decrease in SOA at high UV (~ 100 µg m⁻³) than at low UV (~ 15 µg m⁻³). α -pinene hydroxy dihydroperoxide results from two successive OH reactions and is therefore formed more rapidly and in greater amounts at a higher OH level. α -pinene hydroxy dihydroperoxide in the gas phase with an estimated 3% yield (Eddingsaas et al., 2012a). In the high UV simulation, this compound is formed with >30% yield; therefore, it is likely that reaction pathways leading to this product are overrepresented in GECKO-A.

A second pathway for the reaction of peroxy radicals with HO₂ is formation of an alkoxy and regeneration of OH, added to GECKO-A with an uncertain branching ratio of 20 % and only for peroxy radicals with an oxygenated moiety in the α position. Simulations show that SOA predictions are not sensitive to the second assumption but are very sensitive to the assumed branching ratio for this reaction (Fig. 6). Increasing formation of the alkoxy leads to decreasing SOA formation, with a greater effect at high UV than at low UV. Uncertainty in this branching ratio in the α -pinene system could be a major factor leading to the high/low UV discrepancy.

Finally, Praske et al. (2015) recently identified a third HO₂ reaction channel for peroxy radicals produced from methyl vinyl ketone (MVK): formation of a carbonyl and regeneration of OH and HO₂. In place of a hydroperoxide, which results from the standard HO₂ reaction channel, this reaction produces a ketone, which has a higher vapor pressure and therefore forms less SOA. If this reaction occurs in the α -pinene system, the absence of this pathway in GECKO-A could contribute to SOA overprediction.

Volatilities in this version of GECKO-A are estimated using the Nannoolal et al. (2008) method, which is based on the Clausius-Clapeyron equation. Boiling points are estimated using the Nannoolal et al. (2004, 2008) method with some group contributions taken from Compernolle et al. (2010) (Valorso et al., 2011). Limited experimental data exist for vapor pressures of semi- and low-volatility species, and uncertainty in vapor pressure estimation increases as vapor pressure decreases (Valorso et al., 2011). Therefore, underprediction of vapor pressures for later-generation species could lead to excess SOA. Indeed, Valorso et al. (2011) showed that significant uncertainties in SOA predictions result when using different methods for vapor pressure estimation; however,. While the Nannoolal et al. (2008) method generally led to the highest volatilites and the lowest SOA predictions when compared to the Myrdal and Yalkowsky (1997) method and the SIMPOL-1 method from Pankow and Asher (2008). Therefore, underprediction of vapor pressure is likely not responsible for the enhanced contribution of later-generation species to, each of these methods estimates vapor pressures via a group contribution method (i.e. summing the contributions of all functional groups). If this approach is less accurate for compounds with many functional groups, the volatilities may be underpredicted and these species may be overpredicted in SOA.

A final possible explanation for the overprediction of higher-generation SOA species is that significantly faster vapor wall loss exists for these more functionalized species. Zhang et al. (2015) showed that vapor wall loss rates increase as compound vapor pressure decreases. They measured wall loss rates for primarily first-generation oxidation products to be $10^{-5}-10^{-6} s^{-1}$ in the Caltech chambers. Implementing the k_{gw} parameterization developed by Zhang et al. (2015) in GECKO-A yields similar SOA predictions as those based on assuming a fixed $k_{gw} = 10^{-5} s^{-1}$ (with the exception of the nucleation experiment, in which the k_{gw} parameterization predicted more SOA than using a fixed $k_{gw} = 10^{-5} s^{-1}$). However, it is certainly possible that later generation, more functionalized compounds could exhibit significantly faster wall loss than predicted by the parameterization of Zhang et al. (2015). As one example, Krechmer et al. (2015) fit a wall loss rate of $3 \times 10^{-3} s^{-1}$ for a $C_5 H_{10} O_5$ isoprene oxidation product in the Caltech chambers. If later-generation species in the α -

pinene system exhibit markedly higher wall loss as well, SOA overprediction in GECKO-A would be reduced.

In summary, if GECKO-A overpredicts the contribution of later-generation species, the measurement-model discrepancy at differing UV levels could be reconciledreduced. Reducing the contribution of second-generation species also requires a slower vapor wall loss rate to fit the data, which is actually more consistent with those that have been measured in the Caltech chamber.

5.3 Condensed-phase photolysis

If condensed-phase photolysis occurs in the chamber but is missing in GECKO-A, both the high/low UV measurement-model discrepancy and the high wall loss rate needed to match the 100 % UV observations could potentially be explained. If condensed-phase photolysis is an efficient loss mechanism for SOA at 100 % UV, a lower vapor wall loss rate would be required in order to continue to fit experimental observations. Because condensed-phase photolysis would be less efficient at 10 % UV, under this slower wall loss rate the low UV SOA predictions will increase in the direction of the observations. However, this effect is not seen in the simulations. Figure 7 shows the effect of condensed-phase photolysis, with the radicals produced assumed to be lost permanently. Two wall loss rates are shown, the default $k_{gw} = 10^{-3} s^{-1}$ and a slower $k_{gw} = 10^{-4} s^{-1}$. Only one high UV experiment is shown, but the results are similar for all high UV experiments. Moreover, condensed-phase photolysis has no effect on the low UV predictions (not shown).

At high UV conditions, the assumed presence of condensed-phase photolysis leads to a slight reduction in SOA predictions at the end of the experiment, regardless of k_{gw} . Note that the current implementation of condensed-phase photolysis represents an upper limit: compounds in the condensed phase are taken to photolyze at the same rate as in the gas phase, and fragmentation products are lost permanently. The minor effect of this photolysis upper limit can be explained by comparing the wavelength-dependent photon flux of the chamber to absorption cross sections of species predicted to constitute the SOA (Fig. S9 S11 in the Supplement). Wong et al. (2015) found that the main absorption region of SOA produced by α -pinene ozonolysis corresponds to characteristic absorptions of carbonyl and peroxide functional groups and that the SOA absorption is strongest between 240 and 400 nm. Although products of α -pinene OH oxidation and ozonolysis differ, peroxide and carbonyl functional groups are generated during both (Eddingsaas et al., 2012a). The photon flux in the Caltech chamber is less intense than the solar flux in this region, particularly for the wavelength region over which peroxides photolyze (Fig. S9S11). Because peroxides are expected to be abundant in α -pinene SOA (Capouet et al., 2008; Eddingsaas et al., 2012a), the effect of condensed-phase photolysis may be underrepresented in the Caltech chamber as compared to the atmosphere.

The minor effect of condensed-phase photolysis in these simulations is consistent with the findings of Hodzic et al. (2015), that reduction in SOA from both gas-phase and condensed-phase photolysis for various systems, including α -pinene, is minor during the initial 10 h of a simulation but becomes substantial over a week of atmospheric ageing. Moreover, this result indicates that this process does not explain the high/low UV measurement-model discrepancy. Even in the presence of condensed-phase photolysis, at a wall loss rate $k_{gw} = 10^{-4} \text{ s}^{-1}$ a strong overprediction of SOA still exists at 100 % UV. Although condensed-phase photolysis is potentially important in the atmosphere on longer timescales (Hodzic et al., 2015), it does not explain the low UV measurement-model discrepancy.

5.4 Autoxidation chemistry

Autoxidation has been demonstrated to be important in SOA formation (Crounse et al., 2013; Ehn et al., 2014; Rissanen et al., 2014; Jokinen et al., 2014; Mentel et al., 2015; Rissanen et al., 2015). Formation of extremely low volatile volatility organic compounds (ELVOCs) via autoxidation has been observed from both the OH oxidation and ozonolysis of α -pinene, although in a lower yield than with higher yields observed from ozonolysis (Ehn et al., 2014; Jokinen et al., 2014). In autoxidation, a peroxy radical undergoes an intramolecular hydrogen abstraction to form a hydroperoxide, generating an alkyl radical which then adds oxygen to reform a peroxy radical. This pathway becomes important only when the

rate of hydrogen abstraction is competitive with bimolecular reactions of the peroxy radicals with NO, HO₂, and RO₂ (Crounse et al., 2013). Because lower UV intensities will lead to lower HO₂ and RO₂ concentrations, intramolecular hydrogen abstraction could potentially be favored under low UV. For the high UV experiments, the predicted lifetime with HO₂ is \sim 10 s; for the low UV experiments, \sim 50 s, indicating autoxidation may potentially be more important under low UV.

Moreover, during the low UV experiments, 20-50% of α -pinene reacts with O₃ instead of OH, compared to only 2-3% for the high UV experiments. As discussed previously, the ozonolysis mechanism in GECKO-A is likely incomplete and may be lacking pathways to SOA precursors, such as autoxidation. Because autoxidation is much more efficient from the ozonolysis pathway than from the OH pathway (Ehn et al., 2014; Jokinen et al., 2014), more ELVOCs will likely be produced under low UV and will increase the amount of SOA formed. Furthermore, autoxidation could also explain the difference in SOA yield observed between the two low UV experiments. Experiment 141125 has a higher yield than experiment 141113 and also has a higher observed O₃ concentration. ELVOC production was likely higher during this experiment owing to the increased fraction of α -pinene reacted via ozonolysis.

Autoxidation is observed to occur immediately upon oxidation (Rissanen et al., 2015), indicating it is likely a first-generation process. Second-generation species are predominantly responsible for the discrepancy in model predictions between high and low UV due to the difference in OH levels (Fig. 4). Unlike second-generation products, autoxidation products will not depend on the OH concentration and will not be produced slower under low UV. Therefore, adding autoxidation pathways will likely increase the fraction of SOA composed of first-generation products, which may lead to similar predictions for high and low UV.

However, explicit mechanisms and rate constants are still lacking for autoxidation in the α -pinene system, although they have been developed for simpler cycloalkenes (Mentel et al., 2015; Rissanen et al., 2015). A recent computational study found that the cyclobutyl ring in α -pinene must open in order for intramolecular hydrogen shifts to be competitive with the peroxy bimolecular sink reactions (Kurtén et al., 2015). The currently-accepted α -pinene ozonolysis mechanism does not include rapid opening of this ring. Kurtén et al. (2015) investigated several pathways to break this ring but found none that could explain all of the characteristics of observed ELVOCs from α -pinene. In the absence of these explicit pathways, this hypothesis cannot be currently tested. However, autoxidation remains explicit mechanisms, the effect of autoxidation cannot be fully tested. To approximate the effect, a $C_{10}H_{15}O_9$ species (an ELVOC predicted by Kurtén et al. (2015)) is added with a 7 % molar yield (based on the 6-8 % yield measured by Ehn et al. (2014)) as a direct product from the α -pinene+O₃ reaction. This addition has no effect on SOA concentrations for the high UV experiments but increases the final SOA concentrations for the low UV experiments by $\sim 10 \ \mu g \ m^{-3}$ (not shown). However, adding this fixed ELVOC yield does not increase SOA predictions for low UV at the beginning of the experiment, when no O_3 is present. Therefore, although autoxidation via ozonolysis is likely important towards the end of the low UV experiments, other explanations are needed to reconcile the underprediction of SOA at the start of the experiment. Autoxidation via OH oxidation could potentially resolve part of this discrepancy, but no pathways or yields are yet available. Overall, autoxidation is a likely process to explain the overlap of the growth curves-measurement-model discrepancy at high and low UV but is in need of more study. The presence of significant autoxidation could furthermore lead to a different best-fit vapor wall loss rate.

5.5 Particle-phase dimerization

If dimerization is more competitive with gas-phase fragmentation at the lower OH levels at 10% lights, increased SOA growth could result. Figure 8 shows one 100% UV and one 10% UV experiment with two different values for the dimerization rate constant: $0.01 \text{ M}^{-1} \text{ s}^{-1}$ (Ziemann and Atkinson, 2012; Capouet et al., 2008) and $12 \text{ M}^{-1} \text{ s}^{-1}$ (Shiraiwa et al., 2013) using the same base $k_{gw} = 10^{-3} \text{ s}^{-1}$. The $12 \text{ M}^{-1} \text{ s}^{-1}$ rate constant results in significant SOA overprediction for both the 100% and the 10% UV experiments; the slower dimerization rate constant still results in an overprediction for the 100% UV experiment but an underprediction at 10% UV. For this rate constant, rapid vapor wall loss combined with

the slower chemistry at low UV prevents significant SOA formation, despite dimerization. In the high UV experiment, because gas-phase chemistry occurs faster relative to vapor wall loss, even a slower dimerization rate increases SOA predictions. While dimerization increases SOA predictions for low UV, it has the same effect at high UV. Therefore, dimerization in its current implementation in GECKO-A does not resolve the low UV discrepancy without causing an SOA overprediction for high UV.

5.6 Enhanced wall loss at high UV

To recapitulate, using the base chemistry in GECKO-A, predictions agree with the high UV experiments when using a relatively fast vapor wall loss rate of 10^{-3} s⁻¹, and predictions approximately match the low UV experiments when using a much slower wall loss rate of 10^{-5} s⁻¹. This result prompts the hypothesis that vapor wall loss could somehow be dependent on the UV level. The diffusion coefficient and the eddy diffusivity could change based solely on the UV level if a change in the UV level results in a temperature change in the chamber. The temperature of the chamber was $\sim 3 \text{ K}$ higher for the high UV experiments than for the low. Gas-phase diffusion coefficients are $\sim T^{3/2}$ (Incropera et al., 2007). A 3 K temperature increase will result in an increase in the diffusion coefficient by only a factor of 1.015. The eddy diffusivity characterizes the degree of turbulent mixing in the chamber, which could be increased by temperature variations. When UV lights are turned on, the temperature in the chamber increases by 2-3 K and then gradually decreases to the original temperature from a well-controlled recirculating chilled water system. This small fluctuation is not expected to cause a dramatic increase in turbulence in the chamber. Therefore, increase of vapor wall loss for high UV experiments is deemed incapable of explaining the modeling discrepancy.

6 Atmospheric implications

From the systematic analysis of the experiments and mechanism predictions (and in the absence of explicit autoxidation mechanisms), the most likely hypothesis for two hypotheses could explain some or all of the inability of the base case in GECKO-A to simulate both the high and low UV experiments. The first hypothesis is that later-generation species overcontribute to the SOA in GECKO-A. To compensate for this overcontribution necessitates the assumption of rapid vapor wall loss in order to fit the high UV data; when extended to the low UV experiments, this rapid wall loss results in significant SOA underprediction, since later-generation species are produced more slowly at the lower OH levels. This overcontribution could be the result of several possibilities, each of which has different implications for atmospheric SOA formation. If some reaction pathways are under- or misrepresented in GECKO-A, atmospheric predictions from GECKO-A may then overestimate SOA. If instead all reaction pathways in GECKO-A are realistic but the rates are simply overpredicted, these compounds may still form in the atmosphere but will be affected by competing processes such as dry and wet deposition and uptake into cloud particles (Hodzic et al., 2014; Mouchel-Vallon et al., 2013). If volatilities are too low in GECKO-A, atmospheric predictions would then be biased high. Finally, if higher-generation species simply exhibit a faster wall loss, these compounds will be produced quickly in the atmosphere and will generate significant SOA.

An important implication of our analysis is This hypothesis implies that vapor wall loss in the Caltech chamber is likely slower than that of the base case assumed in GECKO-A. This slower wall loss is consistent with measurements in the Caltech chamber (Loza et al., 2010, 2014; Zhang et al., 2014) but is considerably slower than those measured in the 8 m³ chamber used by Yeh and Ziemann (2015), 10^{-3} – 10^{-4} s⁻¹. Differences in the size and operation of two chambers may contribute to the differences in measured wall loss rates.

The vapor wall loss implied by the present experiments results in an order of magnitude slower rate than that fit by Zhang et al. (2014) during toluene SOA photooxidation. This difference could potentially indicate differences between chemical systems or could also arise from the manner in which the modeling was performed: Zhang et al. (2014) used the Statistical Oxidation Model of Cappa and Wilson (2012) vs. the GECKO-A model used here. An implication of this difference is that the wall loss bias (the ratio of the yield predicted in the absence of vapor wall loss divided by the observed yield) for the α -pinene system is likely

lower than the 1.6 predicted by Zhang et al. (2014). However, because we could not definitively fit here both the high and low UV experiments, we cannot calculate a corresponding wall loss bias.

Autoxidation is likely important in this system and may potentially explain some or all of the overlap of the growth curves at high and low UV The second hypothesis with the potential to explain the measurement-model discrepancy is autoxidation. Autoxidation from both the OH and ozonolysis pathway could be important during the low UV experiments. Explicit mechanisms and rate constants are needed in order to test this hypothesis. If significant, the presence of autoxidation could change the vapor wall loss rate implied by these simulations.

Although other processes do not reconcile the high/low UV model discrepancy, such processes may still be important. Condensed-phase photolysis, though not significant over the short timescale of chamber experiments, has been shown to potentially have a more significant effect in the atmosphere (Hodzic et al., 2015). Particle-phase reactions have been shown to generate significant amounts of high-molecular weight, low volatility species in the α -pinene system (Docherty et al., 2005; Lopez-Hilfiker et al., 2015; Gao et al., 2004b), although more efficiently in ozonolysis (Lopez-Hilfiker et al., 2015). Even if particle-phase dimerization is significant in this system, the assumed irreversible formation of dimers in GECKO-A may not accurately represent particle-phase reactions, which have been suggested to be reversible (Ziemann and Atkinson, 2012; Trump and Donahue, 2014).

The Supplement related to this article is available online at doi:10.5194/acpd-0-1-2016-supplement.

Acknowledgements. This work was supported by National Science Foundation grant AGS-1523500. R. C. McVay acknowledges support by a National Science Foundation Graduate Research Fellowship under Grant No. DGE-1144469. B. Aumont acknowledges support from the French National Research Agency (ANR) under the MAGNIFY project (ANR-14-CE01-0010).

References

- Abramson, E., Imre, D., Beránek, J., Wilson, J. M., and Zelenyuk, A.: Experimental determination of chemical diffusion within secondary organic aerosol particles, Phys. Chem. Chem. Phys., 15, 2983–2991, 2013.
- Atkinson, R. and Arey, J.: Atmospheric degradation of volatile organic compounds, Chem. Rev., 103, 4605–4638, 2003.
- Aumont, B., Szopa, S., and Madronich, S.: Modelling the evolution of organic carbon during its gas-phase tropospheric oxidation: development of an explicit model based on a self generating approach, Atmos. Chem. Phys., 5, 2497–2517, doi:10.5194/acp-5-2497-2005, 2005.
- Bethel, H. L., Atkinson, R., and Arey, J.: Kinetics and products of the reactions of selected diols with the OH radical, Int. J. Chem. Kinet., 33, 310–316, 2001.
- Bian, Q., May, A. A., Kreidenweis, S. M., and Pierce, J. R.: Investigation of particle and vapor wallloss effects on controlled wood-smoke smog-chamber experiments, Atmos. Chem. Phys., 15, 11027–11045, doi:10.5194/acp-15-11027-2015, 2015.
- Birdsall, A. W., Andreoni, J. F., and Elrod, M. J.: Investigation of the role of bicyclic peroxy radicals in the oxidation mechanism of toluene, J. Phys. Chem. A., 114, 10655–10663, 2010.
- Camredon, M., Aumont, B., Lee-Taylor, J., and Madronich, S.: The SOA/VOC/NO_{*x*} system: an explicit model of secondary organic aerosol formation, Atmos. Chem. Phys., 7, 5599–5610, doi:10.5194/acp-7-5599-2007, 2007.
- Cappa, C. D. and Wilson, K. R.: Evolution of organic aerosol mass spectra upon heating: implications for OA phase and partitioning behavior, Atmos. Chem. Phys., 11, 1895–1911, doi:10.5194/acp-11-1895-2011, 2011.
- Cappa, C. D. and Wilson, K. R.: Multi-generation gas-phase oxidation, equilibrium partitioning, and the formation and evolution of secondary organic aerosol, Atmos. Chem. Phys., 12, 9505–9528, doi:10.5194/acp-12-9505-2012, 2012.
- Capouet, M., Peeters, J., Nozière, B., and Müller, J.-F.: Alpha-pinene oxidation by OH: simulations of laboratory experiments, Atmos. Chem. Phys., 4, 2285–2311, doi:10.5194/acp-4-2285-2004, 2004.
- Capouet, M., Müller, J.-F., Ceulemans, K., Compernolle, S., Vereecken, L., and Peeters, J.: Modeling aerosol formation in alpha-pinene photo-oxidation experiments, J. Geophys. Res., 113, D02308, doi:10.1029/2007JD008995, 2008.

- Claeys, M., Iinuma, Y., Szmigielski, R., Surratt, J. D., Blockhuys, F., Van Alsenoy, C., Boge, O., Siereau, B., Gomez-Gonzalez, Y., Vermeylen, R., Van der Veken, P., Shahgholi, M., Chan, A. W. H., Herrmann, H., Seinfeld, J. H., and Maenhaut, W.: Terpenylic acid and related compounds from the oxidation of alpha-pinene: implications for new particle formation and growth above forests, Environ. Sci. Technol., 43, 6976–6982, 2009.
- Compernolle, S., Ceulemans, K., and Müller, J.-F.: Technical Note: Vapor pressure estimation methods applied to secondary organic aerosol constituents from α -pinene oxidation: an intercomparison study, Atmos. Chem. Phys., 10, 6271–6282, doi:10.5194/acp-10-6271-2010, 2010.
- Crounse, J. D., Nielsen, L. B., Jørgensen, S., Kjaergaard, H. G., and Wennberg, P. O.: Autoxidation of organic compounds in the atmosphere, J. Phys. Chem. Lett., 4, 3513–3520, 2013.
- Dillon, T. J. and Crowley, J. N.: Direct detection of OH formation in the reactions of HO₂ with CH₃C(O)O₂ and other substituted peroxy radicals, Atmos. Chem. Phys., 8, 4877–4889, doi:10.5194/acp-8-4877-2008, 2008.
- Docherty, K. S., Wu, W., Lim, Y. B., and Ziemann, P. J.: Contributions of organic peroxides to secondary aerosol formed from reactions of monoterpenes with O₃, Environ. Sci. Technol., 39, 4049– 4059, 2005.
- Donahue, N. M., Henry, K. M., Mentel, T. F., Kiendler-Scharr, A., Spindler, C., Bohn, B., Brauer, T., Dorn, H. P., Fuchs, H., Tillmann, R., Wahner, A., Saathoff, H., Naumann, K. H., Möhler, O., Leisner, T., Müller, L., Reinnig, M. C., Hoffmann, T., Salo, K., Hallquist, M., Frosch, M., Bilde, M., Tritscher, T., Barmet, P., Praplan, A. P., DeCarlo, P. F., Dommen, J., Prévôt, A. S., and Baltensperger, U.: Aging of biogenic secondary organic aerosol via gas-phase OH radical reactions, P. Natl. Acad. Sci. USA, 21, 13503–13508, 2012.
- Eddingsaas, N. C., Loza, C. L., Yee, L. D., Seinfeld, J. H., and Wennberg, P. O.: α-pinene photooxidation under controlled chemical conditions – Part 1: Gas-phase composition in low- and high-NO_x environments, Atmos. Chem. Phys., 12, 6489–6504, doi:10.5194/acp-12-6489-2012, 2012a.
- Eddingsaas, N. C., Loza, C. L., Yee, L. D., Chan, M., Schilling, K. A., Chhabra, P. S., Seinfeld, J. H., and Wennberg, P. O.: α -pinene photooxidation under controlled chemical conditions – Part 2: SOA yield and composition in low- and high-NO_x environments, Atmos. Chem. Phys., 12, 7413–7427, doi:10.5194/acp-12-7413-2012, 2012b.
- Ehn, M., Thornton, J. A., Kleist, E., Sipilä, M., Junninen, H., Pullinen, I., Springer, M., Rubach, F., Tillmann, R., Lee, B., Lopez-Hilfiker, F., Andres, S., Acir, I.-H., Rissanen, M., Jokinen, T., Schobesberger, S., Kangasluoma, J., Kontkanen, J., Nieminen, T., Kurtén, T., Nielsen, L. B., Jørgensen, S., Kjaergaard, H. G., Canagaratna, M., Maso, M. D., Berndt, T., Petäjä, T., Wahner, A., Kerminen, V.-

M. Kulmala, M., Worsnop, D. R., Wildt, J., and Mentel, T. F.: A large source of low-volatility secondary organic aerosol, Nature, 506, 476, 2014.

- Epstein, S. A., Blair, S. L., and Nizkorodov, S. A.: Direct photolysis of *α*-pinene ozonolysis secondary organic aerosol: Effect on particle mass and peroxide content, Environ. Sci. Technol., 48, 11251–11258, 2014.
- Fahnestock, K. A. S., Yee, L. D., Loza, C. L., Coggon, M. M., Schwantes, R., Zhang, X., Dalleska, N. F., and Seinfeld, J. H.: Secondary organic aerosol composition from C₁₂ alkanes, J. Phys. Chem. A., 119, 4281–4297, 2014.
- Gao, S., Ng, N. L., Keywood, M., Varutbangkul, V., Bahreini, R., Nenes, A., He, J., Yoo, K. Y., Beauchamp, J. L., Hodyss, R. P., Flagan, R. C., and Seinfeld, J. H.: Particle phase acidity and oligomer formation in secondary organic aerosol, Environ. Sci. Technol., 38, 6582–6589, 2004a.
- Gao, S., Keywood, M., Ng, N. L., Surratt, J., Varutbangkul, V., Bahreini, R., Flagan, R. C., and Seinfeld, J. H.: Low-molecular-weight and oligomeric components in secondary organic aerosol from the ozonolysis of cycloalkenes and *α*-pinene, J. Phys. Chem. A., 108, 10147–10164, 2004b.
- Griffin, R. J., Cocker III, D. R., Flagan, R. C., and Seinfeld, J. H.: Organic aerosol formation from the oxidation of biogenic hydrocarbons. J. Geophys. Res., 104, 3555–3567, 1999.
- Geunther, A., Hewitt, C. N., Erickson, D., Fall, R., Geron, C., Graedel, T., Harley, P., Klinger, L., Lerdau, M., Mckay, W. A., Pierce, T., Scholes, B., Seinbrecher, R., Tallamraju, R., Taylor, J., and Zimmerman, P.: A global model of natural volatile organic compound emissions, J. Geophys. Res., 100, 8873–8892, 1995.
- Hallquist, M., Wenger, J. C., Baltensperger, U., Rudich, Y., Simpson, D., Claeys, M., Dommen, J., Donahue, N. M., George, C., Goldstein, A. H., Hamilton, J. F., Herrmann, H., Hoffmann, T., linuma, Y., Jang, M., Jenkin, M. E., Jimenez, J. L., Kiendler-Scharr, A., Maenhaut, W., McFiggans, G., Mentel, Th. F., Monod, A., Prévôt, A. S. H., Seinfeld, J. H., Surratt, J. D., Szmigielski, R., and Wildt, J.: The formation, properties and impact of secondary organic aerosol: current and emerging issues, Atmos. Chem. Phys., 9, 5155–5236, doi:10.5194/acp-9-5155-2009, 2009.
- Hasson, A. S., Tyndall, G. S., and Orlando, J. J.: A product yield study of the reaction of HO₂ radicals with ethyl peroxy (C₂H₅O₂), acetyl peroxy (CH₃C(O)O₂), and acetonyl peroxy (CH₃C(O)CH₂O₂), J. Phys. Chem. A., 108, 5979–5989, 2004.
- Hasson, A. S., Kuwata, K. T., Arroyo, M. C., and Petersen, E. B.: Theoretical studies of the reaction of hydroperoxy radicals (HO₂), with ethyl peroxy (C₂H₅O₂), acetyl peroxy (CH₃C(O)O₂) and acetonyl peroxy (CH₃C(O)CH₂O₂) radicals, J. Photoch. Photobio. A., 176, 218–230, 2005.

- Henry, K. M. and Donahue, N. M.: Photochemical aging of *α*-pinene secondary organic aerosol: Effects of OH radical sources and photolysis, J. Phys. Chem. A., 116, 5932–5940, 2012.
- Hodzic, A., Aumont, B., Knote, C., Lee-Taylor, J., Madronich, S., and Tyndall, G.: Volatility dependence of Henry's law constants of condensable organics: application to estimate depositional loss of secondary organic aerosol, Geophys. Res. Lett., 41, 4795–4804, 2014.
- Hodzic, A., Madronich, S., Kasibhatla, P. S., Tyndall, G., Aumont, B., Jimenez, J. L., Lee-Taylor, J., and Orlando, J.: Organic photolysis reactions in tropospheric aerosols: effect on secondary organic aerosol formation and lifetime, Atmos. Chem. Phys., 15, 9253–9269, doi:10.5194/acp-15-9253-2015, 2015.
- Hoffmann, T., Odum, J. R., Bowman, F., Collins, D., Klockow, D., Flagan, R. C., and Seinfeld, J. H.: Formation of organic aerosols from the oxidation of biogenic hydrocarbons, J. Atmos. Chem., 26, 189–222, 1997.
- Incropera, F. P., Dewitt, D. P., Bergman, T. L., and Lavine, A. S.: Fundamentals of Heat and Mass Transfer, 6th Edn., Wiley, Hoboken, NJ, 2007.
- Jimenez, J. L., Canagaratna, M. R., Donahue, N. M., Prévôt, A. S., Zhang, Q., Kroll, J. H., De-Carlo, P. F., Allan, J. D., Coe, H., Ng, N. L., Aiken, A. C., Docherty, K. S., Ulbrich, I. M., Grieshop, A. P., Robinson, A. L., Duplissy, J., Smith, J. D., Wilson, K. R., Lanz, V. A., Hueglin, C., Sun, Y. L., Tian, J., Laaksonen, A., Raatikainen, T., Rautiainen, J., Vaattovaara, P., Ehn, M., Kulmala, M., Tomlinson, J. M., Collins, D. R., Cubison, M. J., Dunlea, E. J., Huffman, J. A., Onasch, T. B., Alfarra, M. R., Williams, P. I., Bower, K., Kondo, Y., Schneider, J., Drewnick, F., Borrmann, S., Weimer, S., Demerjian, K., Salcedo, D., Cottrell, L., Griffin, R., Takami, A., Miyoshi, T., Hatakeyama, S., Shimono, A., Sun, J. Y., Zhang, Y. M., Dzepina, K., Kimmel, J. R., Sueper, D., Jayne, J. T., Herndon, S. C., Trimborn, A. M., Williams, L. R., Wood, E. C., Middlebrook, A. M., Kolb, C. E., Baltensperger, U., and Worsnop, D. R.: Evolution of organic aerosols in the atmosphere, Science, 326, 1525–1529, 2009.
- Jokinen, T., Sipilä, M., Richters, S., Kerminen, V.-M., Paasonen, P., Stratmann, F., Worsnop, D., Kulmala, M., Ehn, M., Herrmann, H., and Berndt, T.: Rapid autoxidation forms highly oxidized RO2 radicals in the atmosphere, Angew. Chem. Int. Edit., 53, 14596–14600, 2014.
- Kalberer, M., Paulsen, D., Sax, M., Steinbacher, M., Dommen, J., Prévôt, A. S. H., Fisseha, R., Weingartner, E., Frankevich, V., Zenobi, R., and Baltensperger, U.: Identification of polymers as major components of atmospheric organic aerosols, Science, 303, 1659–1662, 2004.

- Kamens, R., and Jaoui, M.: Modeling aerosol formation from α -pinene + NO_x in the presence of natural sunlight using gas-phase kinetics and gas-particle partitioning theory, Environ. Sci. Technol., 35, 1394–1405, 2001.
- Kokkola, H., Yli-Pirilä, P., Vesterinen, M., Korhonen, H., Keskinen, H., Romakkaniemi, S., Hao, L., Kortelainen, A., Joutsensaari, J., Worsnop, D. R., Virtanen, A., and Lehtinen, K. E. J.: The role of low volatile organics on secondary organic aerosol formation, Atmos. Chem. Phys., 14, 1689– 1700, doi:10.5194/acp-14-1689-2014, 2014.
- Krechmer, J. E., Coggon, M. M., Massoli, P., Nguyen, T. B., Crounse, J. D., Hu, W., Day, D. A., Tyndall, G. S., Henze, D. V., Rivera-Rios, J. C., Nowak, J. B., Kimmel, J. R., Mauldin III, R. L., Stark, H., Jayne, J. T., Sipilä, M., Junninen, H., St. Clair, J. M., Zhang, X., Feiner, P. A., Zhang, L., Miller, D. O., Brune, W. H., Keutsch, F. N., Wennberg, P. O., Seinfeld, J. H., Worsnop, D. R., Jimenez, J. L., and Canagaratna, M. R.: Formation of low volatility organic compounds and secondary organic aerosol from isoprene hydroxyhydroperoxide low-NO oxidation, Environ. Sci. Technol., 49, 10330–10339, 2015.
- Kurtén, T., Rissanen, M. P., Mackeprang, K., Thornton, J. A., Hyttinen, N., Jørgensen, S., Ehn, M., and Kjaergaard, H.G.: Computational study of hydrogen shifts and ring-opening mechanisms in α-pinene ozonolysis products, J. Phys. Chem. A., 119, 11366–11375, 2015.
- Kuwata, M. and Martin, S. T.: Phase of atmospheric secondary organic material affects its reactivity, P. Natl. Acad. Sci. USA, 109, 17354–17359, 2012.
- Kwok, E. S. C. and Atkinson, R.: Estimation of hydroxyl radical reaction rate constants for gasphase organic compounds using a structure–reactivity relationship: an update, Atmos. Environ., 29, 1685–1695, 1995.
- La, Y. S., Camredon, M., Ziemann, P. J., Valorso, R., Matsunaga, A., Lannuque, V., Lee-Taylor, J., Hodzic, A., Madronich, S., and Aumont, B.: Impact of chamber wall loss of gaseous organic compounds on secondary organic aerosol formation: explicit modeling of SOA formation from alkane and alkene oxidation, Atmos. Chem. Phys. <u>Discuss.</u>, 15, 23893–23930, doi:, 2015., 16, 1417–1431, 2016.
- Lee-Taylor, J., Hodzic, A., Madronich, S., Aumont, B., Camredon, M., and Valorso, R.: Multiday production of condensing organic aerosol mass in urban and forest outflow, Atmos. Chem. Phys., 15, 595–615, doi:10.5194/acp-15-595-2015, 2015.
- Lopez-Hilfiker, F. D., Mohr, C., Ehn, M., Rubach, F., Kleist, E., Wildt, J., Mentel, T. F., Carrasquillo, A. J., Daumit, K. E., Hunter, J. F., Kroll, J. H., Worsnop, D. R., and Thornton, J. A.: Phase partitioning and volatility of secondary organic aerosol components formed from α -pinene

ozonolysis and OH oxidation: the importance of accretion products and other low volatility compounds, Atmos. Chem. Phys., 15, 7765–7776, doi:10.5194/acp-15-7765-2015, 2015.

Loza, C. L., Chan, A. W., Galloway, M. M., Keutsch, F. N., Flagan, R. C., and Seinfeld, J. H.: Characterization of vapor wall loss in laboratory chambers, Environ. Sci. Technol., 44, 5074–5078, 2010.

Loza, C. L., Chhabra, P. S., Yee, L. D., Craven, J. S., Flagan, R. C., and Seinfeld, J. H.: Chemical aging of *m*-xylene secondary organic aerosol: laboratory chamber study, Atmos. Chem. Phys., 12, 151–167, doi:, 2012.

- Loza, C. L., Craven, J. S., Yee, L. D., Coggon, M. M., Schwantes, R. H., Shiraiwa, M., Zhang, X., Schilling, K. A., Ng, N. L., Canagaratna, M. R., Ziemann, P. J., Flagan, R. C., and Seinfeld, J. H.: Secondary organic aerosol yields of 12-carbon alkanes, Atmos. Chem. Phys., 14, 1423–1439, doi:10.5194/acp-14-1423-2014, 2014.
- Ma, Y., Russell, A. T., and Marston, G.: Mechanisms for the formation of secondary organic aerosol components from the gas-phase ozonolysis of α -pinene, Phys. Chem. Chem. Phys., 10, 4294–4312, 2008.
- Mai, H., Shiraiwa, M., Flagan, R. C., and Seinfeld, J. H.: Under what conditions can equilibrium gasparticle partitioning be expected to hold in the atmosphere?, Environ. Sci. Technol., 49, 11485– 11491, 2015.
- Matsunaga, A. and Ziemann, P. J.: Gas-wall partitioning of organic compounds in a teflon film chamber and potential effects on reaction product and aerosol yield measurements. Aerosol Sci. Tech., 44, 881–892, 2010.
- McVay, R. C., Cappa, C. D., and Seinfeld, J. H.: Vapor-wall deposition in chambers: theoretical considerations, Environ. Sci. Technol., 48, 10251–10258, 2014.
- Mentel, T. F., Springer, M., Ehn, M., Kleist, E., Pullinen, I., Kurtén, T., Rissanen, M., Wahner, A., and Wildt, J.: Formation of highly oxidized multifunctional compounds: autoxidation of peroxy radicals formed in the ozonolysis of alkenes – deduced from structure–product relationships, Atmos. Chem. Phys., 15, 6745–6765, doi:10.5194/acp-15-6745-2015, 2015.
- Mouchel-Vallon, C., Bräuer, P., Camredon, M., Valorso, R., Madronich, S., Herrmann, H., and Aumont, B.: Explicit modeling of volatile organic compounds partitioning in the atmospheric aqueous phase, Atmos. Chem. Phys., 13, 1023–1037, doi:10.5194/acp-13-1023-2013, 2013.
- Myrdal, P. B. and Yalkowsky, S. H.: Estimating pure component vapor pressures of complex organic molecules, Ind. Eng. Chem. Res., 36, 2494–2499, 1997.

- Nannoolal, Y., Rarey, J., Ramjugernath, D., and Cordes, W.: Estimation of pure component properties: Part 1. Estimation of the normal boiling point of non-electrolyte organic compounds via group contributions and group interactions, Fluid Phase Equilibr., 226, 45–63, 2004.
- Nannoolal, Y., Rarey, J., and Ramjugernath, D.: Estimation of pure component properties: Part 3: Estimation of the vapor pressure of non-electrolyte organic compounds via group contribution and group interactions, Fluid Phase Equilibr., 269, 117–133, 2008.
- Ng, N. L., Kroll, J. H., Keywood, M. D., Bahreini, R., Varutbangkul, V., Flagan, R. C., Seinfeld, J. H., Lee, A., and Goldstein, A. H.: Contribution of first- versus second-generation products to secondary organic aerosols formed in the oxidation of biogenic hydrocarbons, Environ. Sci. Technol., 40, 2283–2297, 2006.
- Ng, N. L., Chhabra, P. S., Chan, A. W. H., Surratt, J. D., Kroll, J. H., Kwan, A. J., McCabe, D. C., Wennberg, P. O., Sorooshian, A., Murphy, S. M., Dalleska, N. F., Flagan, R. C., and Seinfeld, J. H.: Effect of NO_x level on secondary organic aerosol (SOA) formation from the photooxidation of terpenes, Atmos. Chem. Phys., 7, 5159–5174, doi:10.5194/acp-7-5159-2007, 2007a.
- Ng, N. L., Kroll, J. H., Chan, A. W. H., Chhabra, P. S., Flagan, R. C., and Seinfeld, J. H.: Secondary organic aerosol formation from *m*-xylene, toluene, and benzene, Atmos. Chem. Phys., 7, 3909–3922, doi:10.5194/acp-7-3909-2007, 2007b.
- Nozière, B., Barnes, I., and Becker, K. H.: Product study and mechanisms of the reactions of α -pinene and of pinonaldehyde with OH radicals, J. Geophys. Res., 104, 645–656, 1999.
- Pankow, J. F. and Asher, W. E.: SIMPOL.1: a simple group contribution method for predicting vapor pressures and enthalpies of vaporization of multifunctional organic compounds, Atmos. Chem. Phys., 8, 2773–2796, doi:10.5194/acp-8-2773-2008, 2008.
- Pathak, R. K., Stanier, C. O., Donahue, N. M., and Pandis, S. N.: Ozonolysis of α-pinene at atmospherically relevant concentrations: Temperature dependence of aerosol mass fractions (yields), J. Geophys. Res., 112, D03201, doi:10.1029/2006JD007436, 2007.
- Peeters, J., Vereecken, L., and Fantechi, G.: The detailed mechanism of the OH-initiated atmospheric oxidation of α -pinene: A theoretical study, Phys. Chem. Chem. Phys., 3, 5489–5504, 2001.
- Perraud, V., Bruns, E. A., Ezell, M. J., Johnson, S. N., Yu, Y., Alexander, M. L., Zelenyuk, A., Imre, D., Chang, W. L., Dabdub, D., Pankow, J., and Finlayson-Pitts, B. J.: Nonequilibrium atmospheric secondary organic aerosol formation and growth, P. Natl. Acad. Sci. USA, 109, 2836–2841, 2012.

- Presto, A. A., Huff Hartz, K. E., and Donahue, N. M.: Secondary organic aerosol production from terpene ozonolysis: 1. Effect of UV radiation, Environ. Sci. Technol., 39, 7036–7045, 2005a.
- Presto, A. A., Huff Hartz, K. E., and Donahue, N. M.: Secondary organic aerosol production from terpene ozonolysis: 2. Effect of NO_x concentration, Environ. Sci. Technol., 39, 7046–7054, 2005b.
- Pye, H. O. T., Chan, A. W. H., Barkley, M. P., and Seinfeld, J. H.: Global modeling of organic aerosol: the importance of reactive nitrogen (NO_x and NO₃), Atmos. Chem. Phys., 10, 11261–11276, doi:10.5194/acp-10-11261-2010, 2010.
- Renbaum-Wolff, L., Grayson, J. W., Bateman, A. P., Kuwata, M., Sellier, M., Murray, B. M., Shilling, J. E., Martin, S. T., and Bertram, A. K.: Viscosity of *α*-pinene secondary organic material and implications for particle growth and reactivity, P. Natl. Acad. Sci. USA, 110, 8014–8019, 2013.
- Rissanen, M. P., Kurtén, T., Sipilä, M., Thornton, J. A., Kangasluoma, J., Sarnela, N., Junninen, H., Jørgensen, S., Schallhart, S., Kajos, M. K., Taipale, R., Springer, M., Mentel, T. F., Ruuskanen, T., Petäjä, T., Worsnop, D. R., Kjaergaard, H. G., and Ehn, M.: The formation of highly oxidized multifunctional products in the ozonolysis of cyclohexene, J. Am. Chem. Soc., 136, 15596–15606, 2014.
- Rissanen, M. P., Kurtén, T., Sipilä, M., Thornton, J. A., Kausiala, O., Garmash, O., Kjaergaard, H. G., Petäjä, T., Worsnop, D. R., Ehn, M., and Kulmala, M.: Effects of chemical complexity on the autoxidation mechanisms of endocyclic alkene ozonolysis products: from methylcyclohexenes toward understanding α -pinene, J. Phys. Chem., 119, 4633–4650, 2015.
- Saleh, R., Donahue, N. M., and Robinson, A. L.: Time scales for gas-particle partitioning equilibration of secondary organic aerosol formed from alpha-pinene ozonolysis, Environ. Sci. Technol., 47, 5588–5594, 2013.
- Saukko, E., Lambe, A. T., Massoli, P., Koop, T., Wright, J. P., Croasdale, D. R., Pedernera, D. A., Onasch, T. B., Laaksonen, A., Davidovits, P., Worsnop, D. R., and Virtanen, A.: Humiditydependent phase state of SOA particles from biogenic and anthropogenic precursors, Atmos. Chem. Phys., 12, 7517–7529, doi:10.5194/acp-12-7517-2012, 2012.
- Seinfeld, J. H. and Pandis, S. N.: Atmospheric Chemistry and Physics: From Air Pollution to Climate Change, 2nd Edn. Wiley, Hoboken, N. J., 2006.

- Shiraiwa, M., Yee, L. D., Schilling, K. A., Loza, C. L., Craven, J. S., Zuen, A., Ziemann, P. J., and Seinfeld, J. H.: Size distribution dynamics reveal particle-phase chemistry in organic aerosol formation, P. Natl. Acad. Sci. USA., 110, 11746–11750, 2013.
- Takekawa, H., Minoura, H., and Yamazaki, S.: Temperature dependence of secondary organic aerosol formation by photo-oxidation of hydrocarbons, Atmos. Environ., 37, 3413–3424, 2003.
- Tobias, H. J., and Ziemann, P. J.: Kinetics of the gas-phase reactions of alcohols, aldehydes, carboxylic acids, and water with the C13 stabilized Criegee intermediate formed from ozonolysis of 1-tetradecene, J. Phys. Chem. A., 105, 6129–6135, 2001.
- Tolocka, M. P., Jang, M., Ginter, J. M., Cox, F. J., Kamens, R. M., and Johnston, M. V.: Formation of oligomers in secondary organic aerosol, Environ. Sci. Technol., 38, 1428–1434, 2004.
- Trump, E. R. and Donahue, N. M: Oligomer formation within secondary organic aerosols: equilibrium and dynamic considerations, Atmos. Chem. Phys., 14, 3691–3701, doi:10.5194/acp-14-3691-2014, 2014.
- Vaden, T. D., Song, C., Zaveri, R. A., Imre, D., and Zelenyuk, A.: Morphology of mixed primary and secondary organic particles and the adsorption of spectator organic gases during aerosol formation, P. Natl. Acad. Sci. USA, 107, 6658–6663, 2010.
- Vaden, T. D., Imre, D., Beránek, J., Shrivastava, M., and Zelenyuk, A.: Evaporation kinetics and phase of laboratory and ambient secondary organic aerosol, P. Natl. Acad. Sci. USA, 108, 2190–2195, 2011.
- Valorso, R., Aumont, B., Camredon, M., Raventos-Duran, T., Mouchel-Vallon, C., Ng, N. L., Seinfeld, J. H., Lee-Taylor, J., and Madronich, S.: Explicit modelling of SOA formation from *α*-pinene photooxidation: sensitivity to vapour pressure estimation, Atmos. Chem. Phys., 11, 6895–6910, doi:10.5194/acp-11-6895-2011, 2011.
- Vereecken, L., Müller, J.-F., and Peeters, J.: Low-volatility poly-oxygenates in the OH-initiated atmospheric degradation of *alpha*-pinene: impact of non-traditional peroxy radical chemistry, Phys. Chem. Chem. Phys., 9, 5241–5248, 2007.
- Virtanen, A., Joutsensaari, J., Koop, T., Kannosto, J., Yli-Pirilä, P., Leskinen, J., Mäkelä, J. M., Holopainen, J. K., Pöschl, U., Kulmala, M., Worsnop, D. R., and Laaksonen, A.: An amorphous solid state of biogenic secondary organic aerosol particles, Nature, 467, 824–827, 2010.

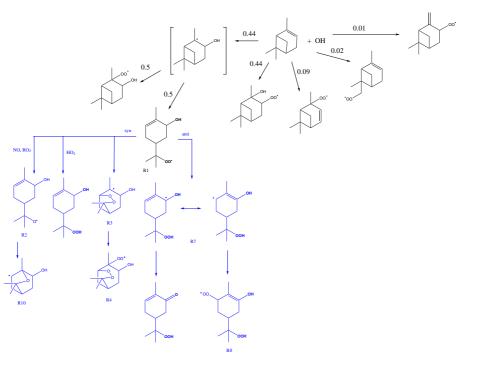
- Wong, J. P. S., Zhou, S., and Abbatt, P. D.: Changes in secondary organic aerosol composition and mass due to photolysis: relative humidity dependence, J. Phys. Chem. A., 119, 4309–4316, 2015.
- Yee, L. D., Craven, J. S., Loza, C. L., Schilling, K. A., Ng, N. L., Canagaratna, M. R., Ziemann, P. J., Flagan, R. C., and Seinfeld, J. H.: Effect of chemical structure on secondary organic aerosol formation from C₁₂ alkanes, Atmos. Chem. Phys., 13, 11121–11140, doi:10.5194/acp-13-11121-2013, 2013.
- Yeh, G. K. and Ziemann, P. J.: Alkyl nitrate formation from the reactions of C₈-C₁₄ *n*-alkanes with OH radicals in the presence of NO_x: measured yields with essential corrections for gas-wall partitioning, J. Phys. Chem. A., 118, 8147–8157, 2014.
- Yeh, G. K. and Ziemann, P. J.: Gas-wall partitioning of oxygenated organic compounds: measurements, structure-activity relationships, and correlation with gas chromatographic retention factor, Aerosol. Sci. Tech., 49, 727–738, 2015.
- Zhang, X., Cappa, C. D., Jathar, S. H., McVay, R. C., Ensberg, J. J., Kleeman, M. J., and Seinfeld, J. H.: Influence of vapor wall-loss in laboratory chambers on yields of secondary organic aerosol, P. Natl. Acad. Sci. USA, 111, 5802–5807, doi:10.1073/pnas.1404727111, 2014.
- Zhang, X., Schwantes, R. H., McVay, R. C., Lignell, H., Coggon, M. M., Flagan, R. C., and Seinfeld, J. H.: Vapor wall deposition in Teflon chambers, Atmos. Chem. Phys., 15, 4197–4214, doi:10.5194/acp-15-4197-2015, 2015.
- Ziemann, P. J. and Atkinson, R.: Kinetics, products, and mechanisms of secondary organic aerosol formation, Chem. Soc. Rev., 41, 6582–6605, 2012.

Expt.	Desc.	T (K)	RH (%)	HC_0	Initial Seed Surface	Duration
				(ppb)	Area (μ m ² cm ⁻³)	(min)
141007	Nucleation	300	< 5 %	51	0	300
				•	-	
141016	Low SA	300	< 5 %	56	$1.7 imes10^3$	534
141028	Med SA	300	< 5 %	53	$3.2 imes 10^3$	233
141118	High SA	298	< 5 %	51	$3.4 imes10^3$	410
	3 -					
141113	10 % UV, Low SA	297	< 5 %	53	$9.9 imes10^2$	1070
141125	10 % UV, Med SA	297	< 5 %	49	$2.4 imes10^3$	1160
	,					

 Table 1. Initial conditions for photooxidation experiments.

Figure 1. Overview of the α -pinene + OH oxidation mechanism in GECKO-A. Reactions in black are those originally implemented in Valorso et al. (2011). Additions to this mechanism are shown in blue. Species are labeled to be consistent with Vereecken et al. (2007). All subsequent chemistry is generated in GECKO-A according to the standard protocols in GECKO-A.

Discussion Paper



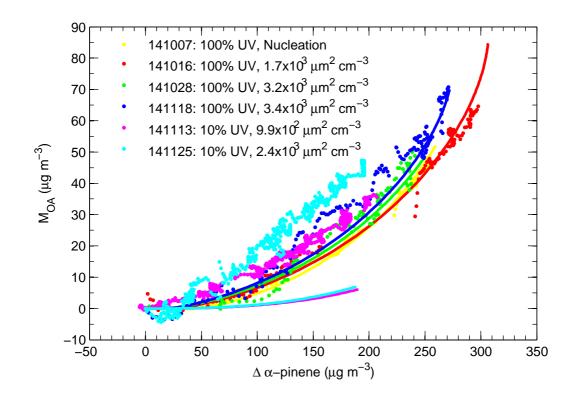


Figure 2. Mass of SOA, M_{OA} , as a function of reacted α -pinene. Experimental data are shown with filled circles, with colors corresponding to individual experiments (see Table 1), and have been corrected for particle wall loss (see text). Predictions using the default GECKO-A are shown as solid lines with the colors corresponding to the different experiments. In GECKO-A, the vapor-particle accommodation coefficient is set to $\alpha_p = 1$ and the vapor wall loss rate is set to $k_{gw} = 10^{-3} s^{-1}$.

Schematic illustrating various explanations of the behavior of the SOA growth curves at high and low UV conditions (high vs. low OH). Horizontal lines at the top of each panel denote the chamber wall. Dashed vs. solid and thick vs. thin lines illustrate differences in relative rates for various processes. Panel 1: low rate of vapor wall loss (dashed lines). Dashed lines in low UV reaction sequence indicate slower chemistry due to lower OH levels. Panel 2: later-generation OH reaction rate constants reduced to approximate a lesser contribution of later-generation species to SOA (thinner reaction arrows). Panel 3: condensed-phase photolysis is included, which will be more efficient at high UV. Panel 4: fast vapor wall loss (solid lines). Autoxidation is favored under low UV owing to longer peroxy lifetimes. Panel 5: particle-phase dimerization included. Panel 6: rate of vapor wall loss faster at high UV (solid lines) than low UV (dashed lines) owing to temperature or turbulence effects.

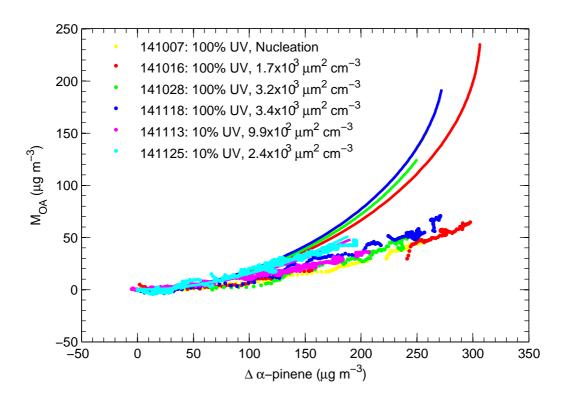
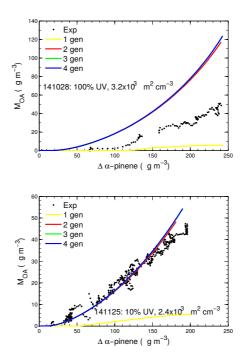


Figure 3. Mass of SOA as a function of reacted α -pinene. Experimental data are shown as filled circles. Solid lines correspond to GECKO-A predictions using a vapor wall loss rate $k_{gw} = 10^{-5} \text{ s}^{-1}$.

Discussion Paper



Discussion Paper

Figure 4. Mass of SOA as a function of reacted α -pinene. Experimental data are shown with filled circles. Solid lines correspond to GECKO-A predictions from different generations of reaction using a vapor wall loss rate $k_{gw} = 10^{-5} \text{ s}^{-1}$, where a generation corresponds to reaction with OH up to formation of a stable product.

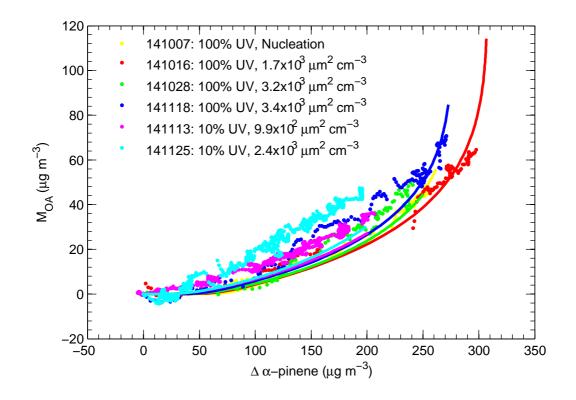


Figure 5. Mass of SOA as a function of reacted α -pinene. Experimental data are shown with filled circles. Solid lines display GECKO-A predictions when using OH reaction rate constants that have been reduced to 10% of their default values (with the exception of α -pinene + OH) and $k_{gw} = 10^{-5} s^{-1}$.

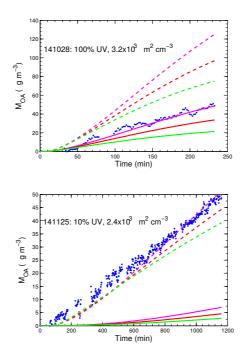


Figure 6. Mass of SOA as a function of time for one 100% UV and one 10% UV experiment. Experimental data are shown with filled circles. Lines show GECKO-A predictions when varying the branching ratio for the $RO_2 + HO_2$ reaction with differing vapor wall loss rates. Solid lines show predictions with $k_{gw} = 10^{-3} \text{ s}^{-1}$, and dashed lines show predictions with $k_{gw} = 10^{-5} \text{ s}^{-1}$. Pink lines show the base case predictions, in which the branching between formation of the hydroperoxide and the alkoxy from $RO_2 + HO_2$ is 80:20. For the red lines, the branching ratio is 50:50, and for the green, it is 25:75.

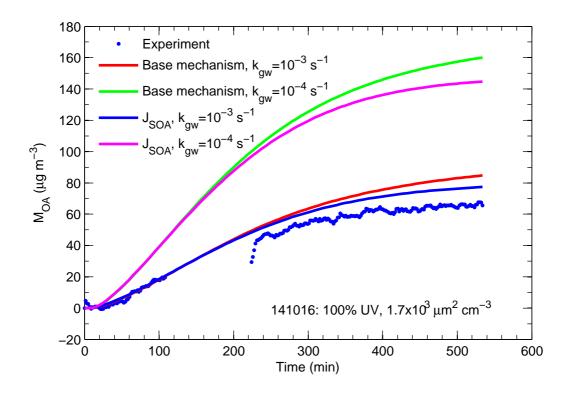


Figure 7. Mass of SOA as a function of time for one 100 % UV experiment. Experimental data are shown with filled circles. Solid lines show GECKO-A predictions with and without condensed-phase photolysis with two different vapor wall loss rates.

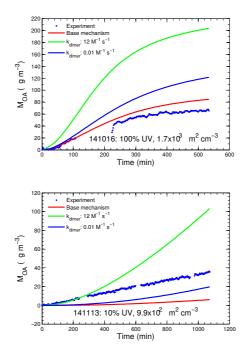


Figure 8. Mass of SOA as a function of time for one 100% UV experiment and one 10% experiment. Experimental data are shown with filled circles. Solid lines show GECKO-A predictions for the base case and then with two values of a condensed-phase dimerization rate constant, all simulations using $k_{gw} = 10^{-3} s^{-1}$.